



DE LA RECHERCHE À L'INDUSTRIE

cea



ERAM module



HA-TPC



[www.cea.fr](http://www.cea.fr)

# T2K/ND280 HA-TPC

## ENCAPSULATED RESISTIVE ANODE MICROMEAS DETECTOR

D. Attié, S. Bolognesi, D. Calvet, P. Colas, **A. Delbart**,  
S. Emery, S. Hassani, M. Lehuraux, J. Porthault,  
M. Riallot, F. Rossi, S. Suvorov  
*CEA/DSM-IRFU, Univ. Paris – Saclay*

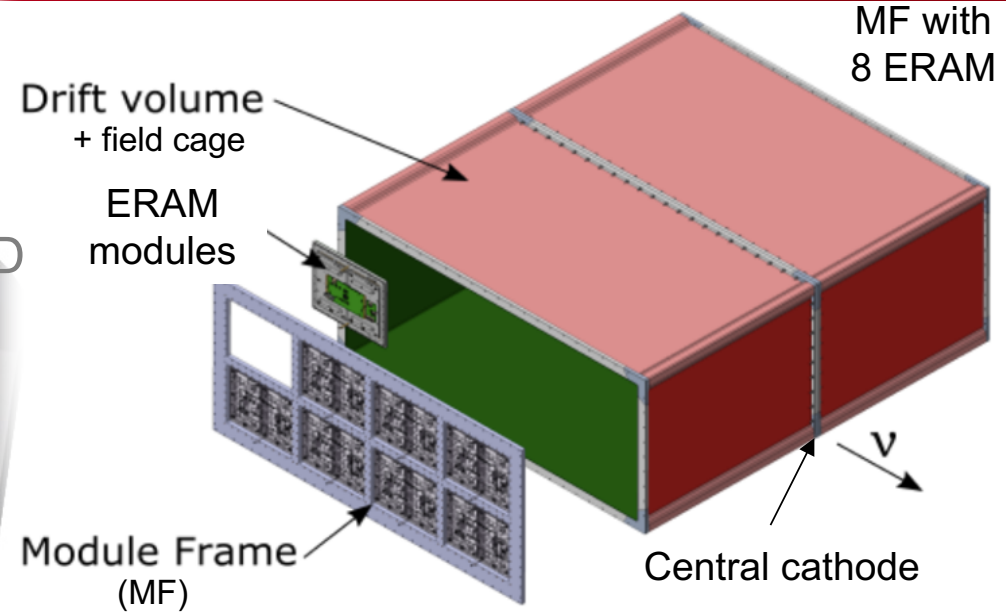
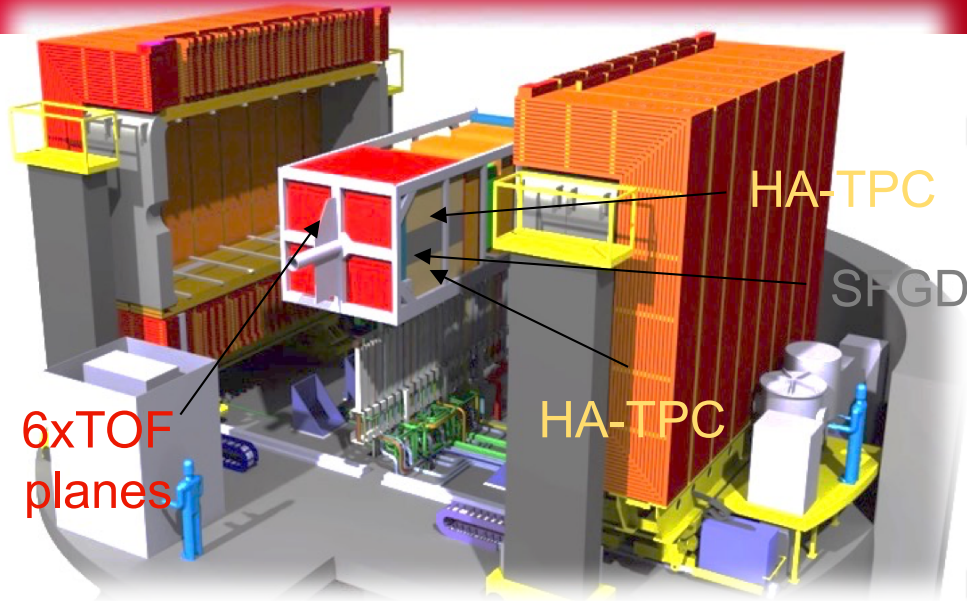
R. De Oliveira, B. Mehl, O. Pizzirusso,  
*CERN-EP-DT-EF, MPGD Lab.*

*Within the T2K/ND280 - HA-TPC collaboration*

## ERAM : Encapsulated Resistive Anode Micromegas

- ND280 upgrade ERAM modules history
- 2019 MM1 & 2020 ERAM#1 prototypes
  - DLC resistivity measurements
  - Beam tests (CERN & DESY)
  - First operation of an ERAM with its final FEE

## HA-TPCS

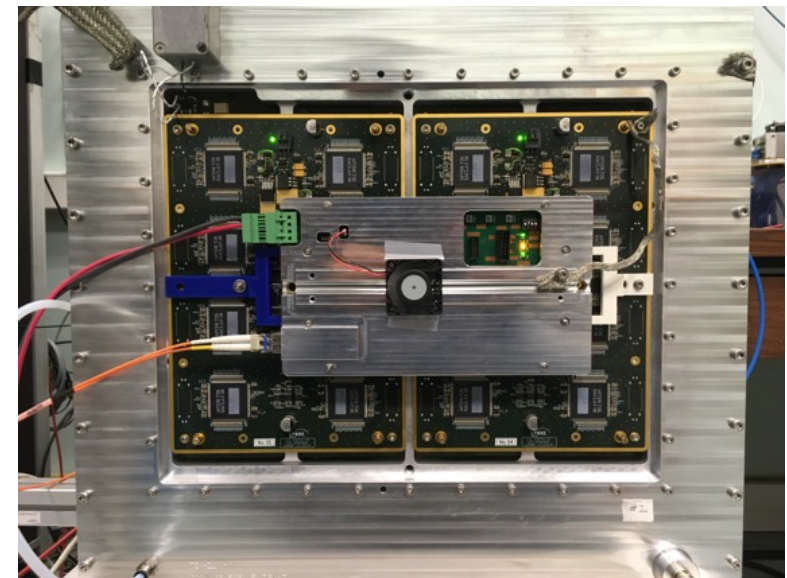


MF with 8 ERAM

2x T2K/ HA-TPC (2022)    3x T2K/ V-TPC (2010)

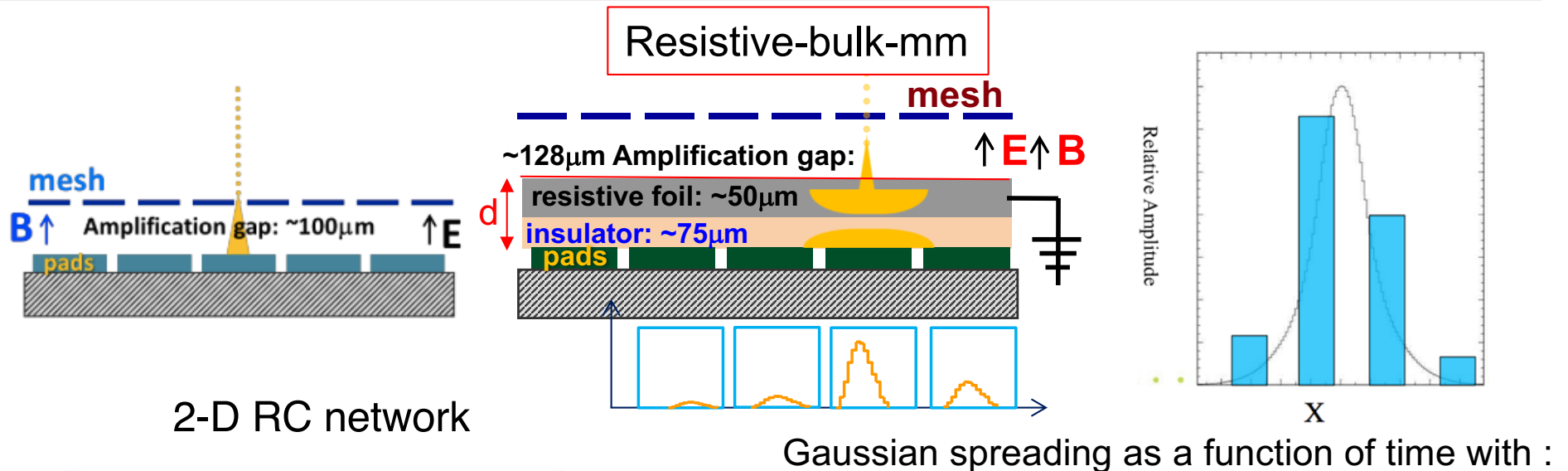
Parameter	Value	
Overall x × y × z (m)	2.0 × 0.8 × 1.8	0.85 × 2.2 × 1.8
Drift distance (cm)	90	
Magnetic Field (T)	0.2	
Electric field (V/cm)	275	
Gas Ar-CF <sub>4</sub> -iC <sub>4</sub> H <sub>10</sub> (%)	95 - 3 - 2	
Drift Velocity <i>cm/μs</i>	7.8	
Transverse diffusion ( <i>μm/√cm</i> )	265	
Micromegas gain	1000	
Micromegas dim. z×y (mm)	340x420 (32)	340x360 (72)
Pad z × y (mm)	10 × 11	7x10
N pads	36864	124272
el. noise (ENC)	800	
S/N	100	
Sampling frequency (MHz)	25	
N time samples	511	

T2K HA-TPC ERAM module (2020)



## Choice of the Resistive foil technology for the HA-TPC micromegas readout

- Charge spreading which should enable keeping the ~600 μm spatial resolution with larger pads and improves it at short drift distance → less electronic channels, cost reduction
- ASIC spark protection no longer needed → more compact FEE, maximize HA-TPC acceptance
- Encapsulated mesh @ GND + insulating layer → potentially lower track distortions & better S/N



$$\rho(r, t) = \frac{RC}{2t} \exp\left[-\frac{r^2 RC}{4t}\right]$$

R- surface resistivity  
C- capacitance/unit area



$$\sigma_r = \sqrt{\frac{2t}{RC}} \left\{ \begin{array}{l} t \approx \text{shaping time (few 100 ns)} \\ RC_{[ns/mm^2]} = \frac{180 R_{[M\Omega/\blacksquare]}}{d_{[\mu m]}/175} \end{array} \right.$$

For pads of ~11x10 mm<sup>2</sup>, the Kapton foil resistivity could be **around 0.4 MΩ/■** and glue thickness **~75 μm** for a good charge spreading (σ~ 5 mm) RC **~50 ns/mm<sup>2</sup>**

Version	Delivery date	pad number (Y x Z) Pad size (mm) FE Type	DLC R (Mohm) foil	DLC R (Mohm) detector	Glue thick. ( $\mu\text{m}$ ) (not measured)	RC (ns/mm <sup>2</sup> )	expected sigma (mm) for 200 ns peaking time	Goal	Main results
<i>R&amp;D (MM0)</i> <i>T2K v-TPC design</i> <i>34 x 36 cm<sup>2</sup></i>	<i>2018</i>	<i>36 x 38 (1726)</i> <i>6.9 x 9.7</i> <i>T2k v-TPC</i>						<i>charge spreading testing</i>	
MM0-DLC1	january 2018		2.5 (not measured)	?	200	310	1,6	tested on HARP TPC @ CERN (08/2018) Nucl Instrum Meth A 957 (july 2019)	Manufacturing procedure validation achieved required performances for 412ns peaking NIM A957 (july 2019) <a href="https://doi.org/10.1016/j.nima.2019.163286">10.1016/j.nima.2019.163286</a>
MM0-DLC2	june 2018		2.5 (not measured)	?	200	310	1,6		
MM0-DLC3#1	november 2018		0.29 to 0.40 foil #2/7	~0.2	75	50	4,0	destroyed after connector soldering	bulk delamination after 216°C soldering
MM0-DLC3#2	january 2019		0.4 to 0.66 foil #2/7	0.40 to 0.64	75	100 to 159	2,2 to 2,8	at INFN	7/24 wrong connectors ! Non reproducible Resistivity change during manufacturing process
<i>Pre-design (MM1)</i> <i>34 x 42 cm<sup>2</sup></i>	<i>2019</i>	<i>32 x 36 (1152)</i> <i>10.09 x 11.18</i> <i>ARC</i>						<i>Final size / first RC optimization</i> <i>FEE connection + shielding</i> <i>validation</i>	
MM1-DLC1	april 2019		0.32 to 0.44 foil #7/7	0.2 to 0.27	75	50 to 67	3,5 to 4	tests at DESY 2019 tests on single-RMM 2019 prototype @ CERN (EHN1)	Detector / FEE interface validation Manufacturing process control achieved required performances for 412 ns peaking time
MM1-DLC2	june 2019		0.32 to 0.43 foil #5/7	0.2 to 0.27	75	50 to 67	3,5 to 4	FEE cooling mock-up (feb 2020-)	to be compared to DLC1
<i>Pre-series (ERAM)</i> <i>34 x 42 cm<sup>2</sup></i>	<i>2020</i>	<i>32 x 36 (1152)</i> <i>10.09 x 11.18</i> <i>ARC &amp; Final FEE V1</i>						<i>Final design / Last RC optimization</i> <i>for 200 ns peaking time</i>	
ERAM #01 (S/N002)	january 2020		0.28 to 0.40 foil #3/7	0.16 to 0.22	200	20 to 27	5,4 to 6,3	Desy test beam (oct 2020)	First cosmic tracks on june 10 with final FEE
ERAM#2	30 august 2020 ?				TbC			Possible use of new DLC foils	
<i>ERAM production</i> <i>34 x 42 cm<sup>2</sup></i>	<i>dec 2020</i> <i>to feb 2022</i>	<i>32 x 36 (1152)</i> <i>10.09 x 11.18</i> <i>Final FEE</i>							
ERAM #03-#10	feb 2021		goal : same ERAM #01 with better uniformity		TbC			New DLC foil production better R uniformity ?	first new DLC batch (7 foils) received 16 february (R x 2 !)



Name	2018 MM0-DLC#	2019 MM1-DLC#	2020 ERAM#
Readout PCB	Original T2K-TPC	HA-TPC	HA-TPC V2 + final FEE
Size	34 × 36 cm <sup>2</sup>	34 × 42 cm <sup>2</sup>	34 × 42 cm <sup>2</sup>
Pads	48 × 36 cm <sup>2</sup>	32 × 36 cm <sup>2</sup>	32 × 36 cm <sup>2</sup>
Pad size	6,85 × 9,65 mm <sup>2</sup>	10,09 × 11,18 mm <sup>2</sup>	10,09 × 11,18 mm <sup>2</sup>
Pad number	1728	1152	1152
Isolation layers	75 -200 μm glue + 50 μm APICAL	75 μm glue + 50 μm APICAL	200 μm glue + 50 μm APICAL

Expected charge Spreading:

• MM0-DLC1 (2,5 MΩ/sq):  
 $\sigma \sim 1,6 \text{ mm for } t=400 \text{ ns}$

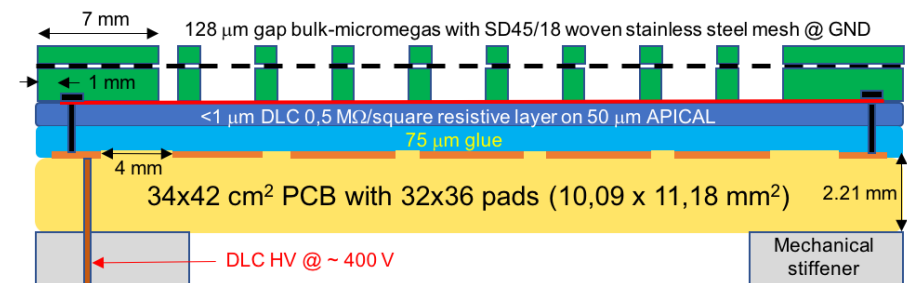
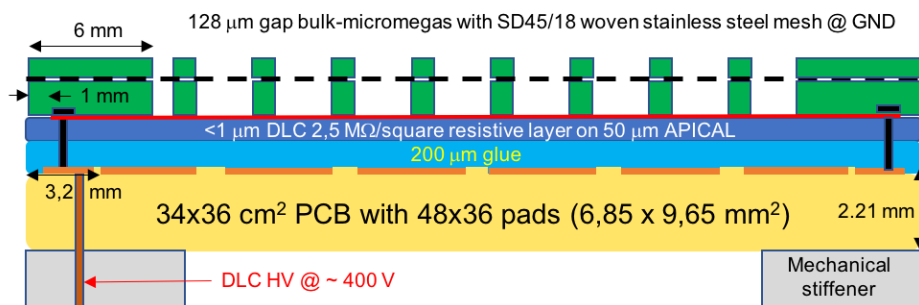
• MM1-DLC1 (~0,25 MΩ/sq):  
 $\sigma \sim 2,5 \text{ mm for } t=200 \text{ ns}$   
 $\sigma \sim 3,5 \text{ mm for } t=400 \text{ ns}$

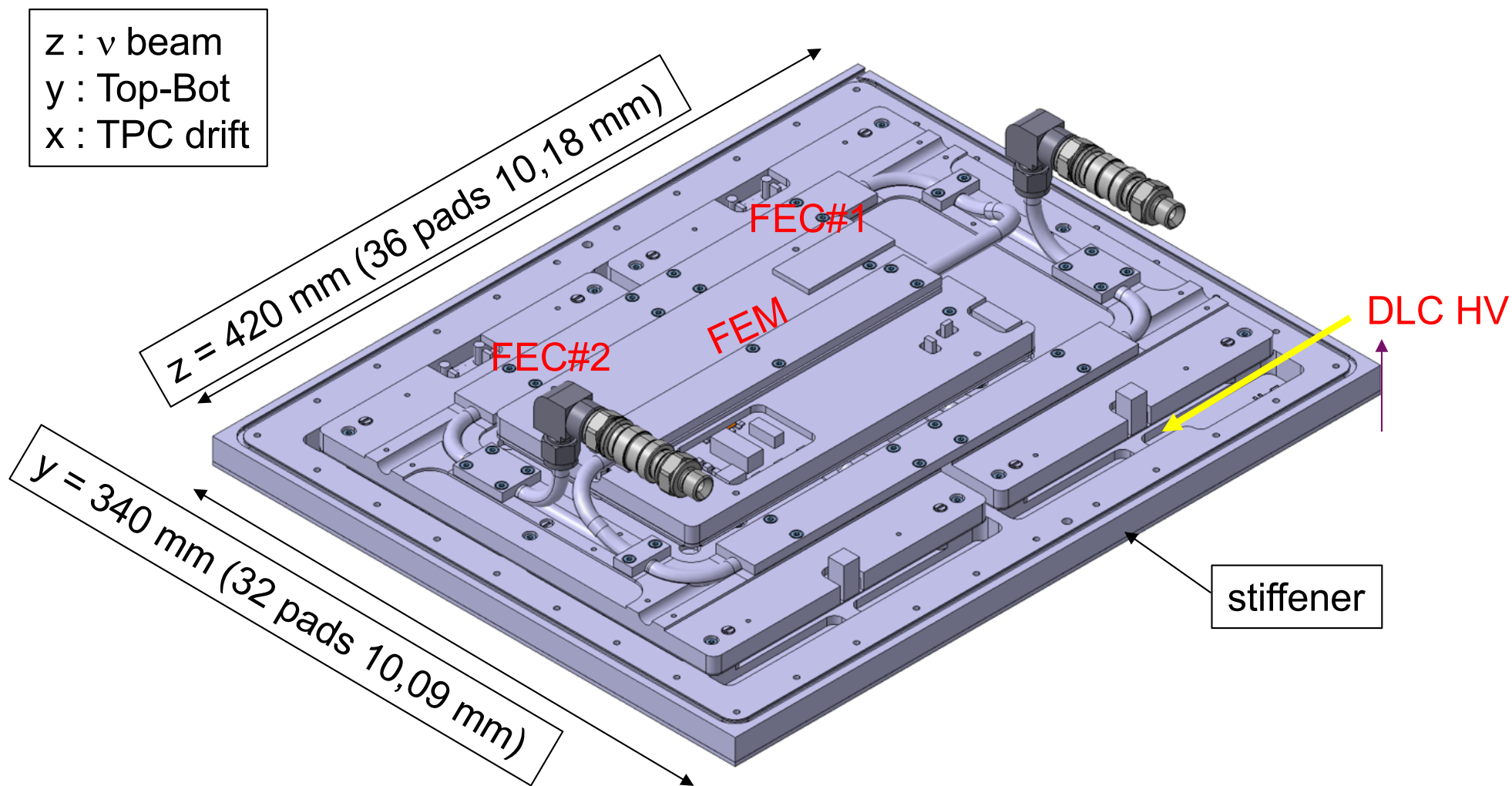
• ERAM#1 (~0,2 MΩ/sq):  
 $\sigma \sim 4,2 \text{ mm for } t=200 \text{ ns}$   
 $\sigma \sim 6 \text{ mm for } t=400 \text{ ns}$

2018 CERN test beam : 2-3 pads  
Multiplicity, ~320 μm @ 30 cm drift  
2x better than non-resistive 2010 TPCs

2019 DESY test beam

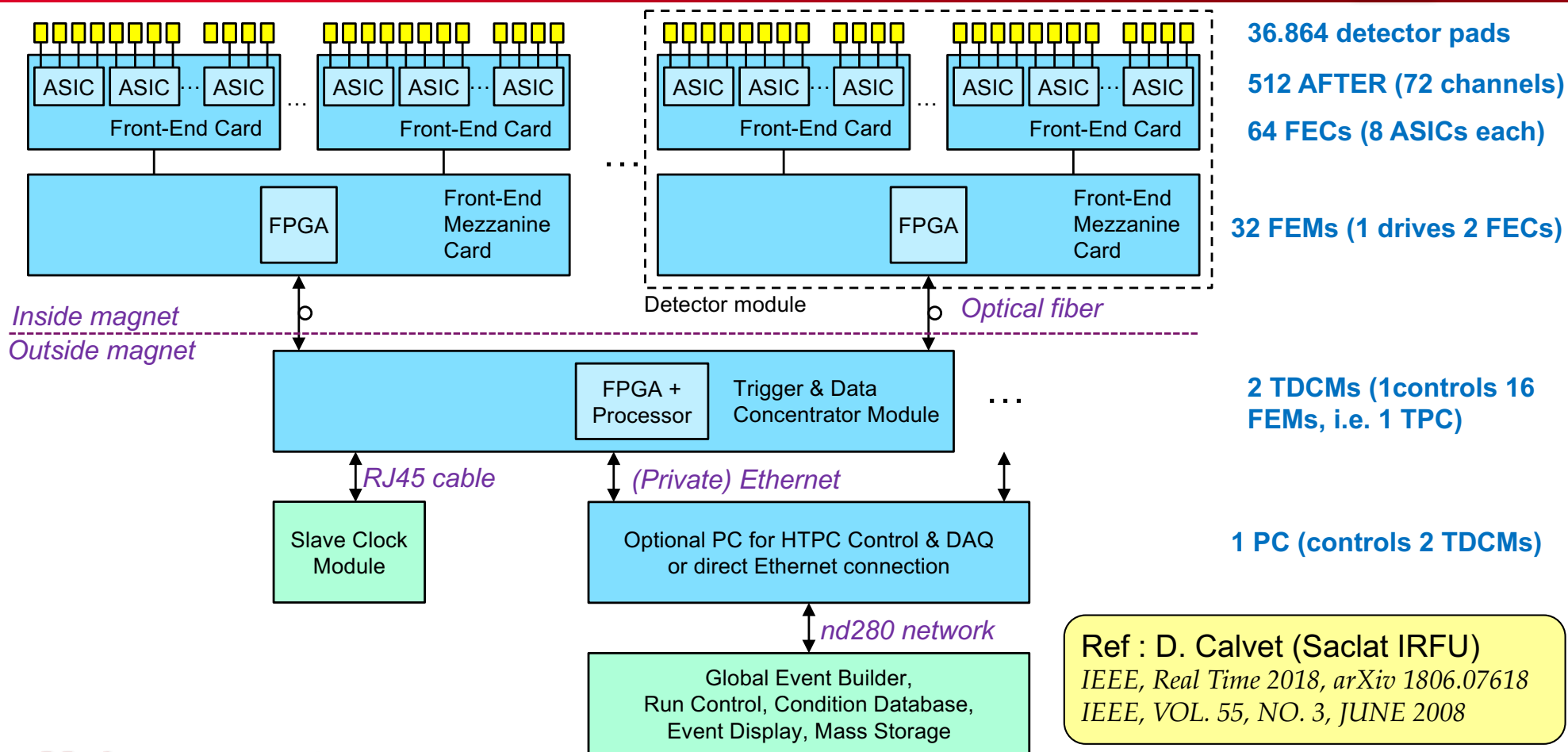
Oct 2020 DESY test  
On-going data taking  
with cosmics





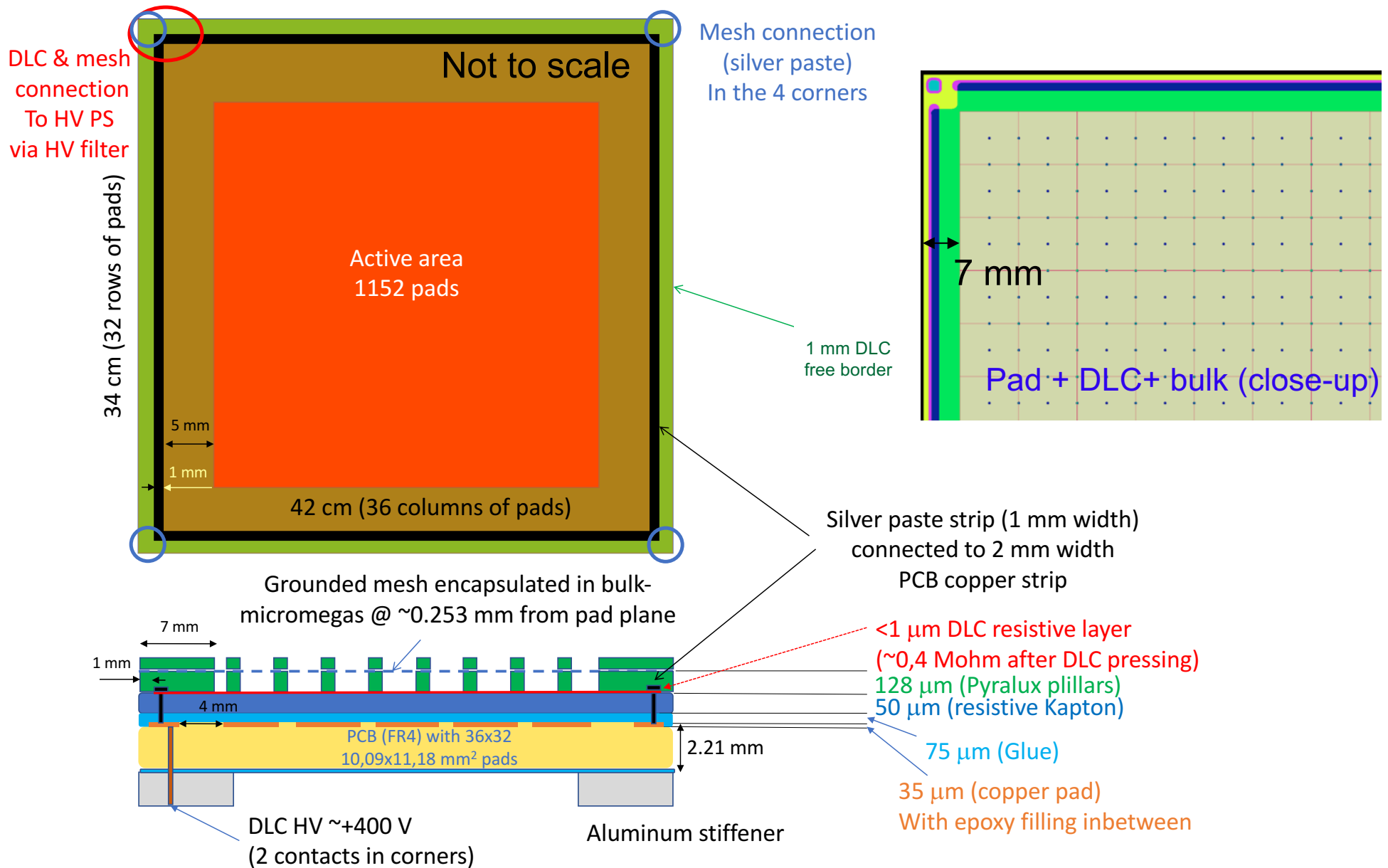
Total x thickness < 20 mm

Ref: J. Porthaul/F. Rossi (Saclay Irfu)  
H. Przybilski (IFJ-PAN)



## Main concepts

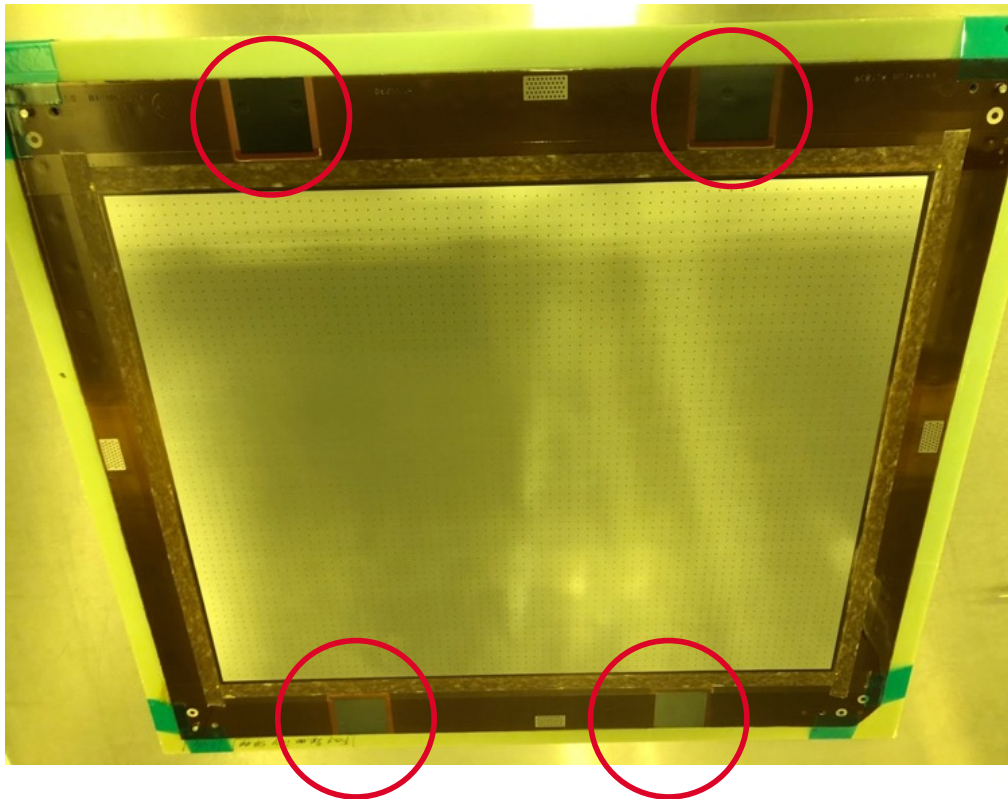
- AFTER chip designed for T2K (511 bucket SCA sampling@25 MHz, 120fC-600 fC, 100ns-2μs peaking time)
- New FEC with 8 AFTER chips which digitizes pad signal with an 8 ch. ADC (minimum dead time of 3.3 ms)
- FEM provides control (&trigger), synchronization, data aggregation, data buffering & data zero suppression
- The TDCM is a generic clock and trigger distributor and data aggregator (FPGA+2 xilinx CPU+1 GB DDR3)



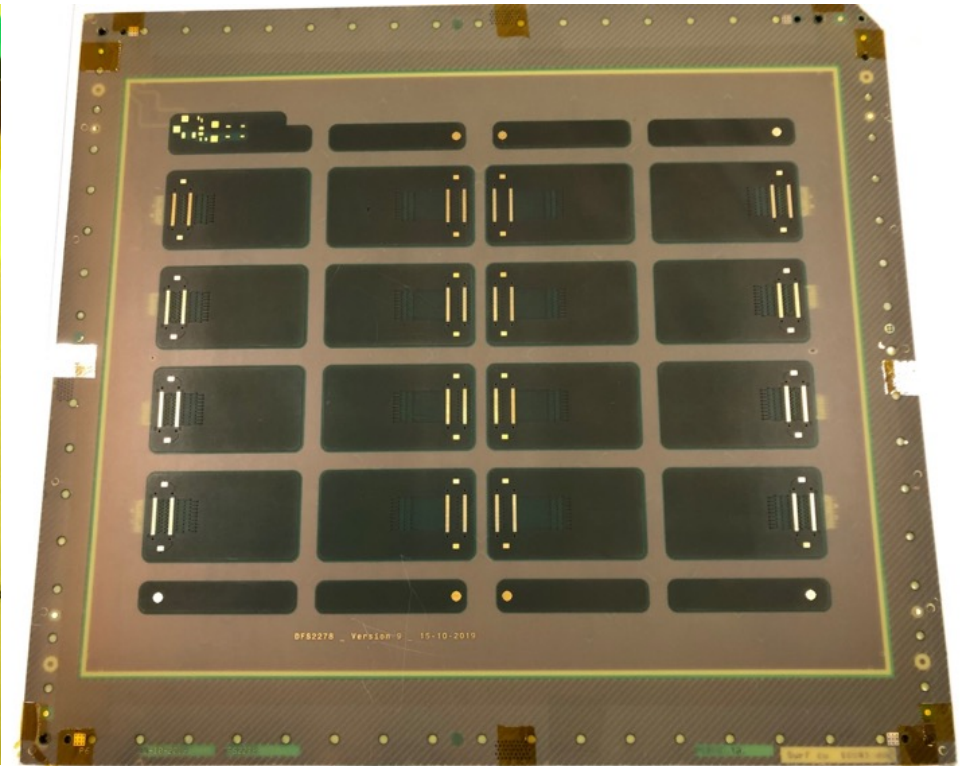


## ERAM#1 before connector soldering

4 zones to measure final detector DLC resistivity



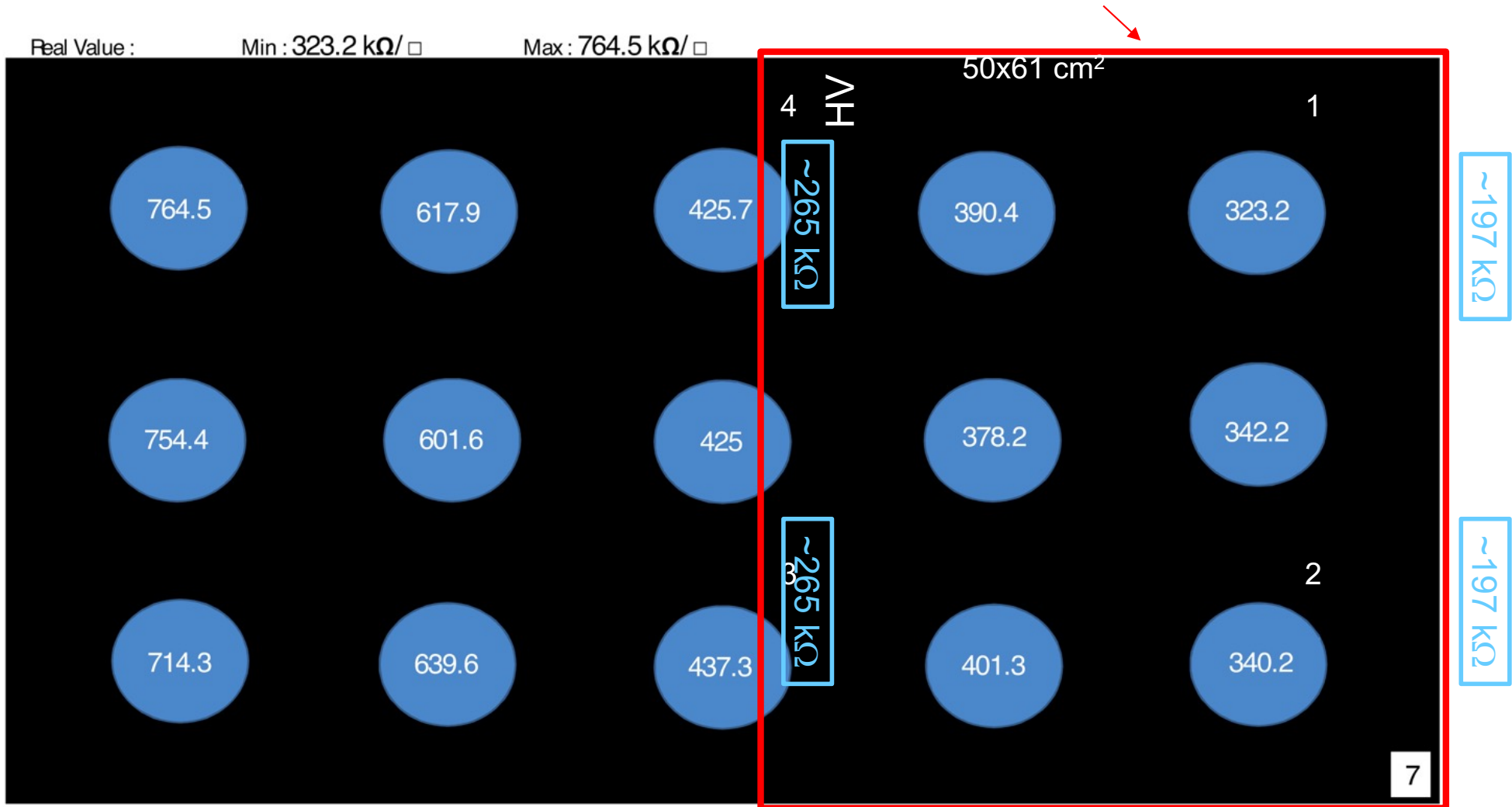
Bulk-micromegas side



Connector side

DLC was polarized @ 850V in air with a measured current of 7 à 8 nA.

Part of DLC foil #7 used for MM1-DLC1



In blue : measured value outside detector area once detector is finished  
~60% drop after DLC foil pressing & connector soldering

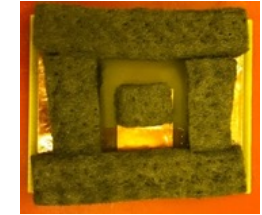
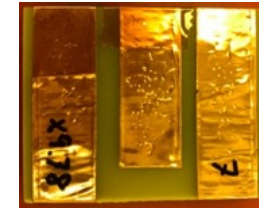
MM1-DLC1 resistivity – active area side (CERN "ochi" probe, k=6,79)

PCB N°2 - MM1-DLC N°1  
feuille N°7

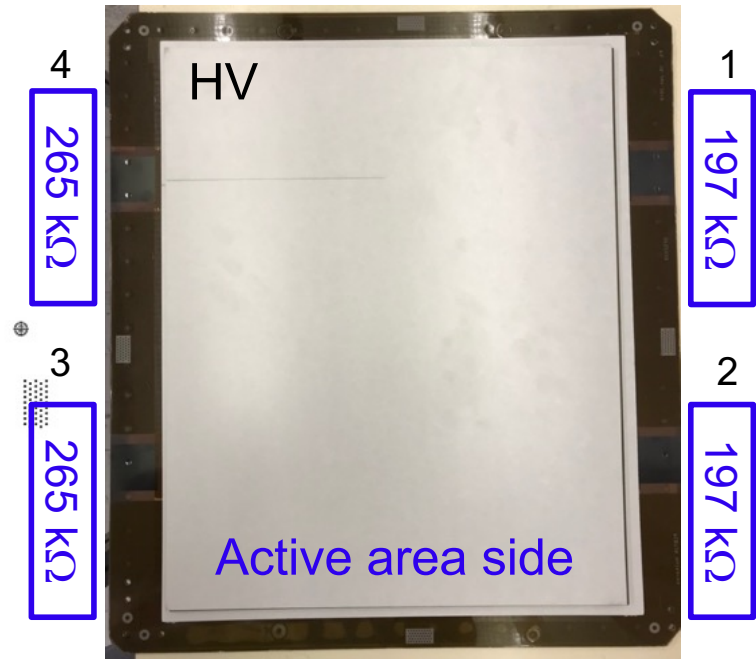
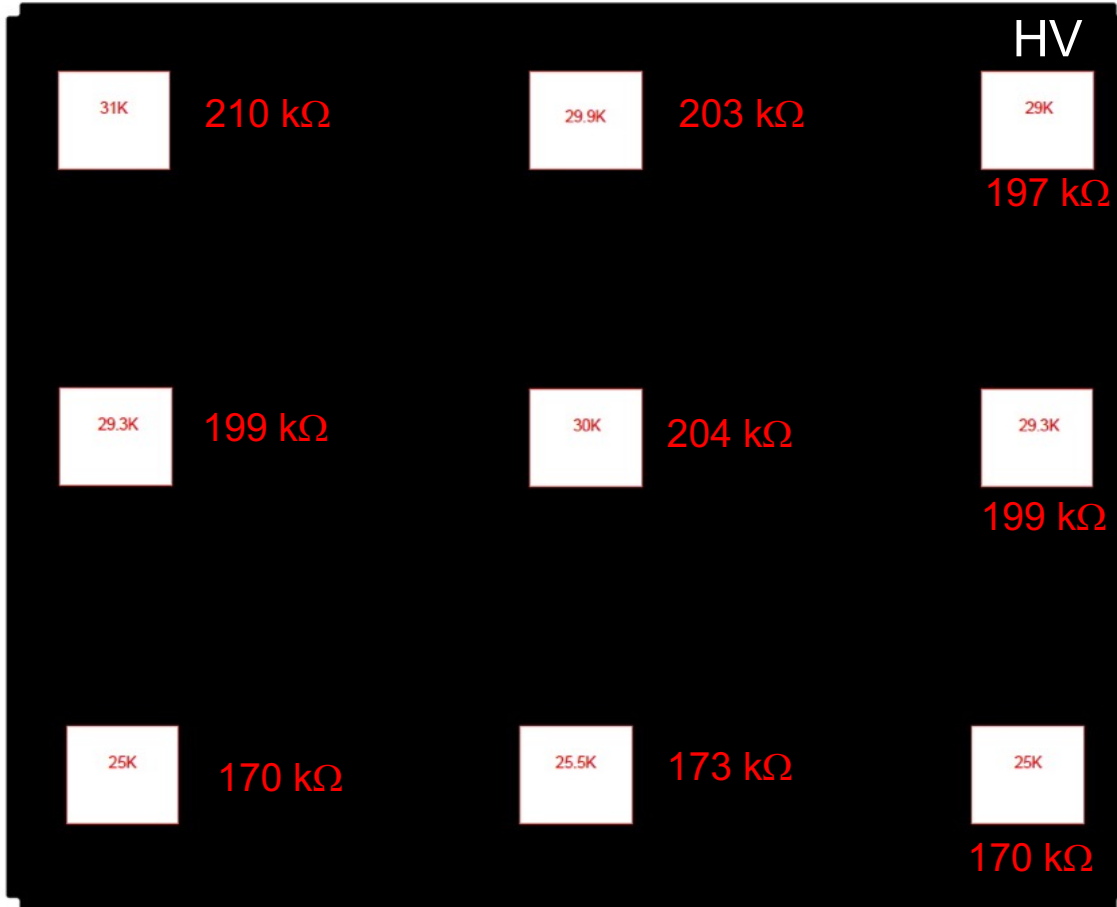
Les valeurs affichees ne tiennent pas compte du coefficient de l'appareil qui est de 6.79

221 kΩ (32.6K, 39K) / 265 kΩ (3/)

222 kΩ (32.7K, 39K) / 265 kΩ (4/)



MM1-DLC1 resistivity



Foil#5 used for MM1-DLC2  
 → Same resistivity within 10%  
 → Same Final resistivity

Mesures avant pressage (black)

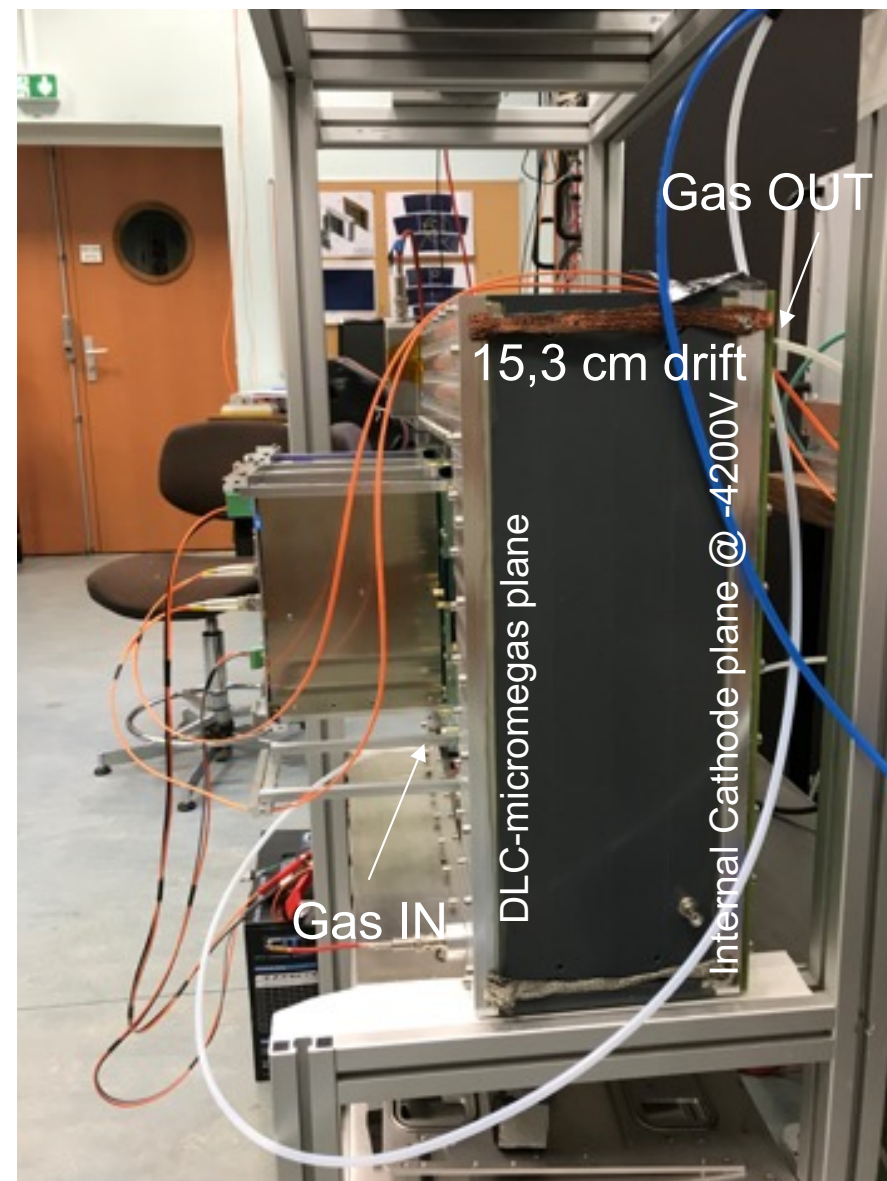
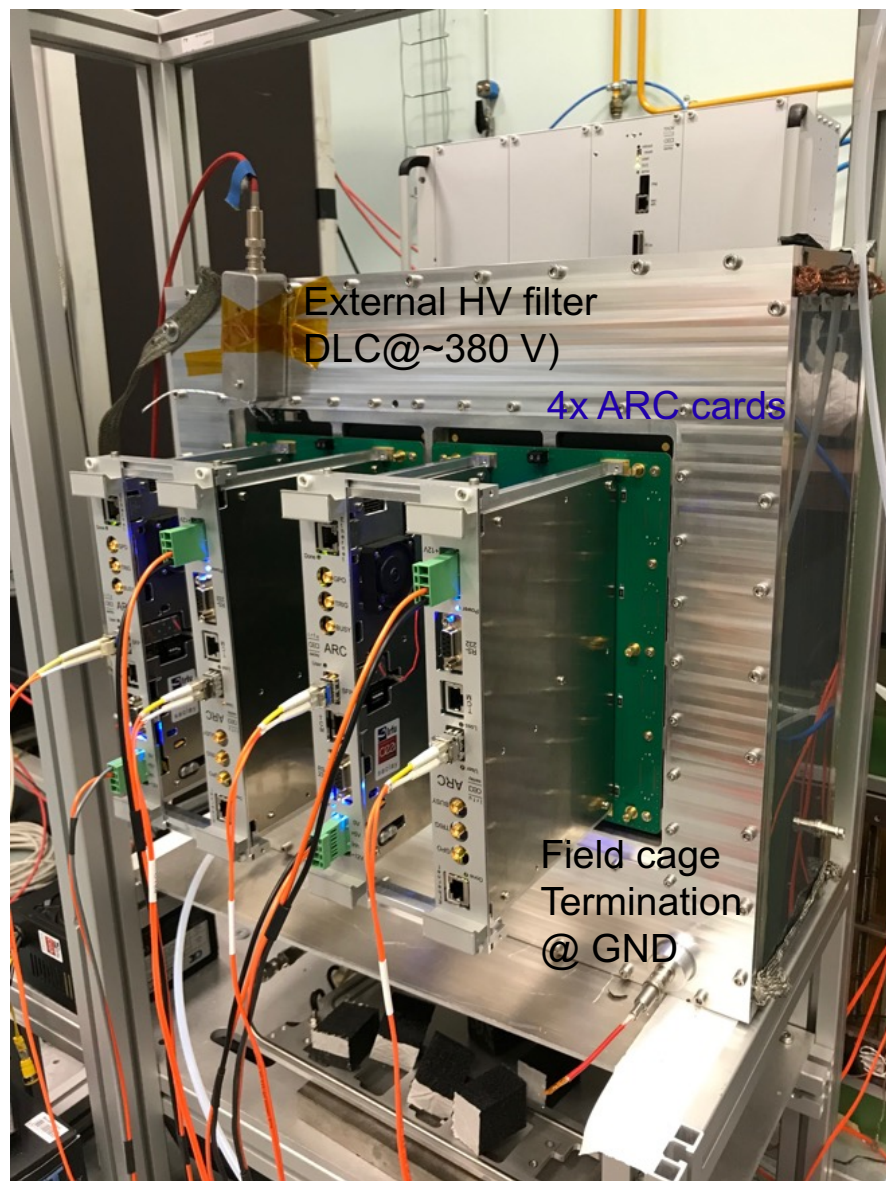
Mesures après pressage (red)

Mesures après soudage (blue)

166 kΩ (24.4K, 29K) / 197 kΩ (2/)

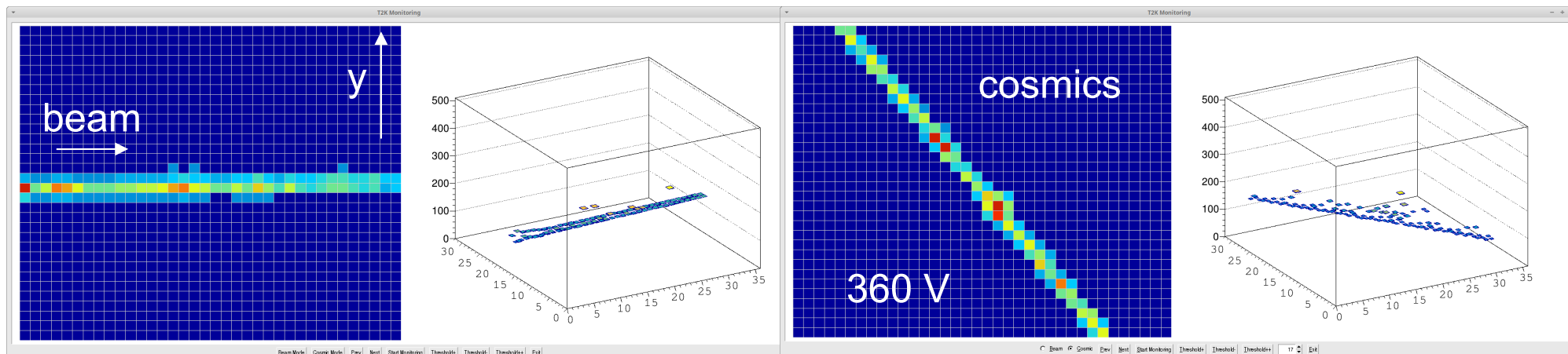
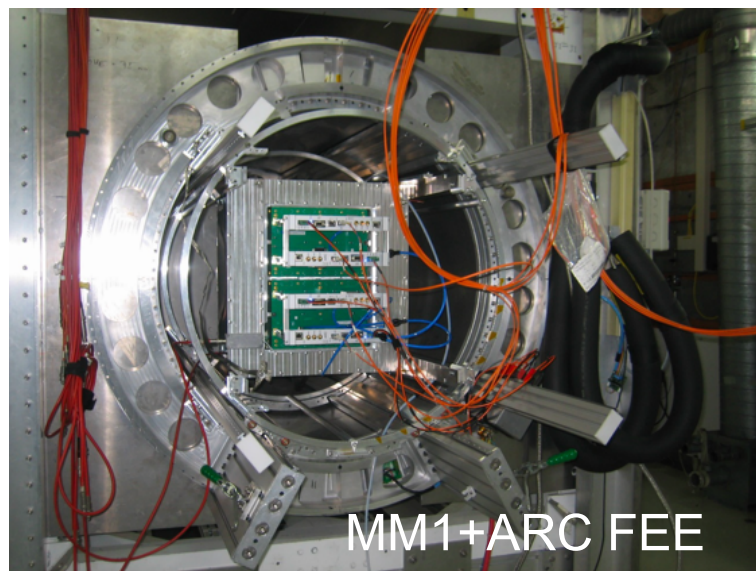
170 kΩ (25K, 29K) / 197 kΩ (1/)





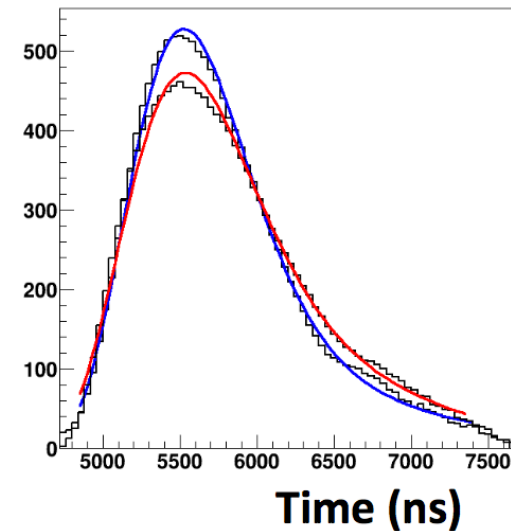
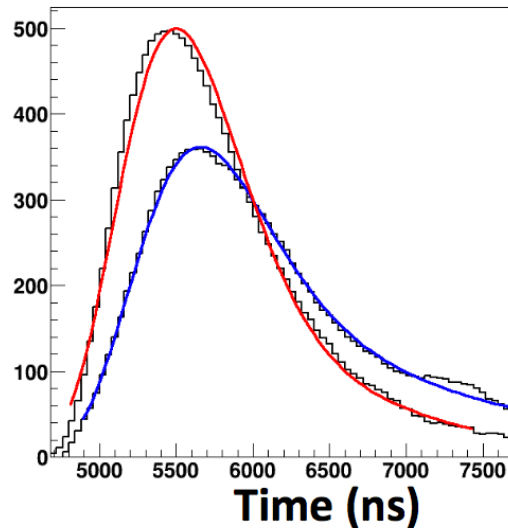
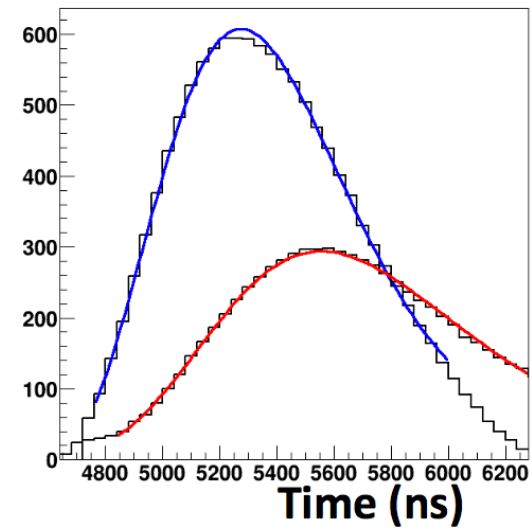
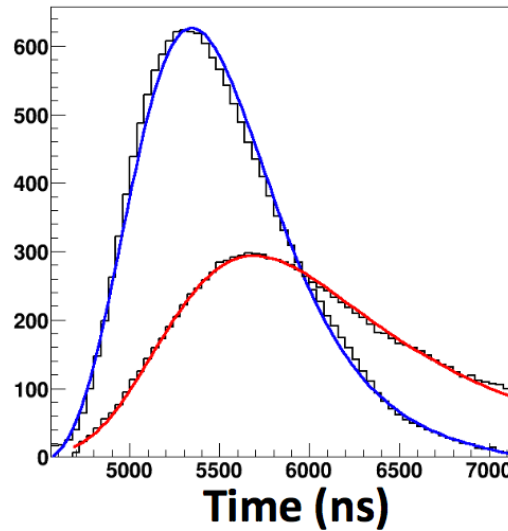
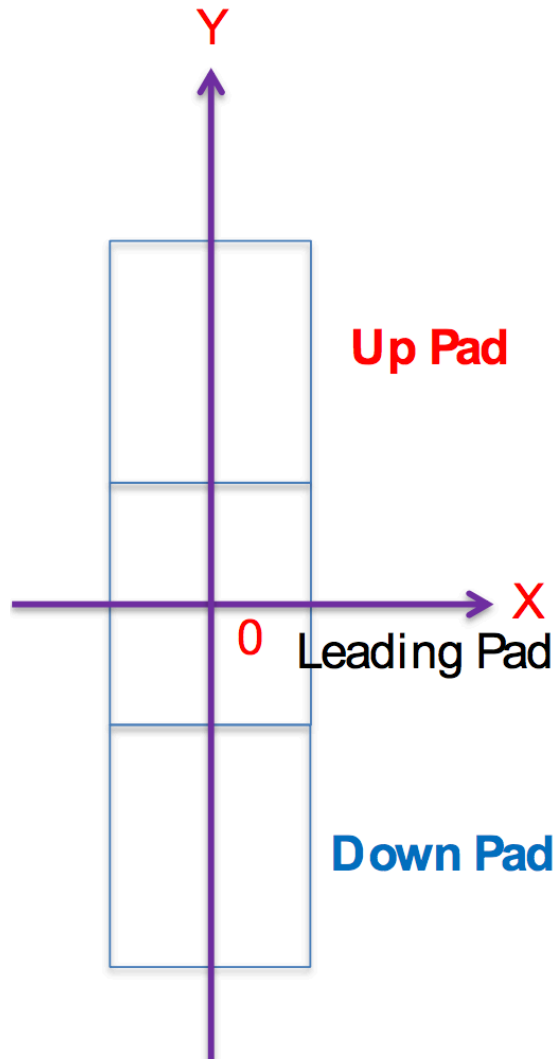


- T2K gas Argon(95%)/CF<sub>4</sub>(3%)/isobutane(2%), 280 V/cm drift field
- Front-end electronics : 4 x 288-channel ARCv2-AFTER
- 4 GeV e- beam, PCMAG magnet set @ 0,2 T (ND280 B field)



## Down resistive pad ; Up resistive pad

Ref : S. Hassani / S. Emery (Saclay Irfu)

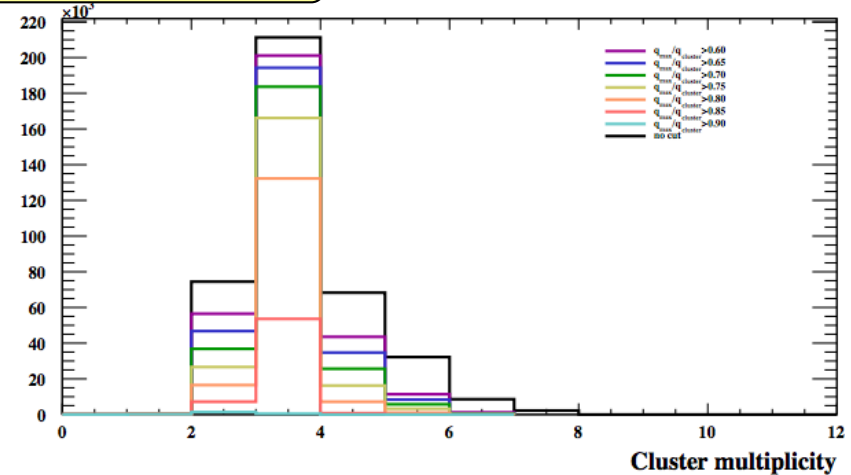
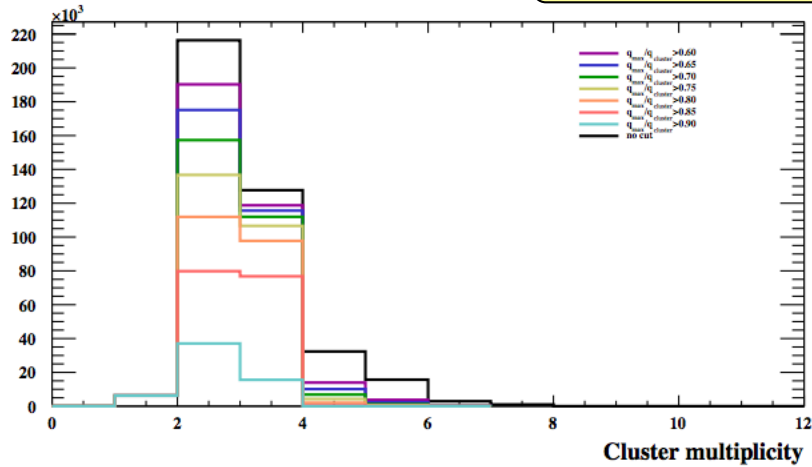


On-going work to extract RC map

Peaking Time = 116 ns

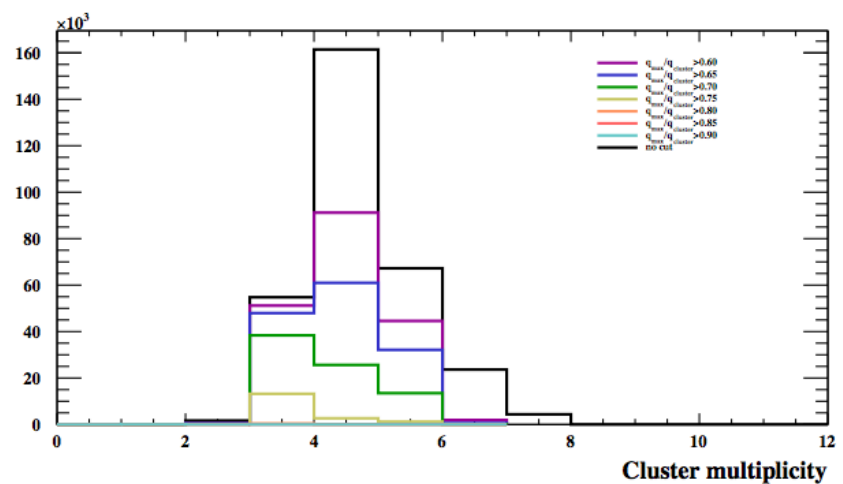
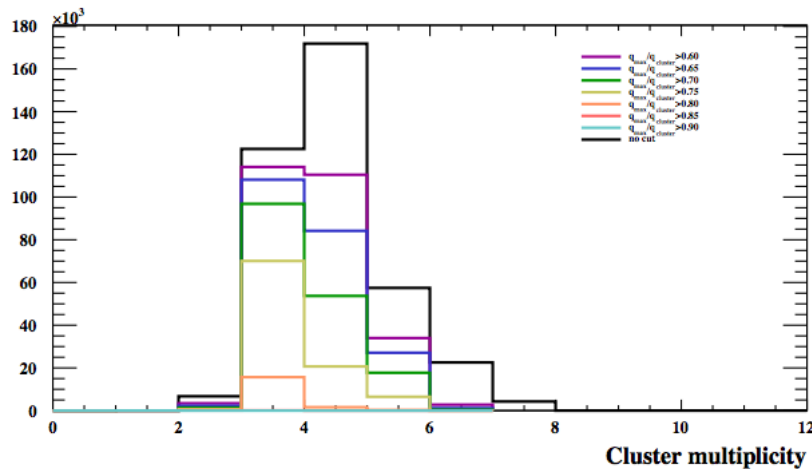
Peaking Time = 200 ns

Ref : S. Hassani / S. Emery (Saclay Irfu)

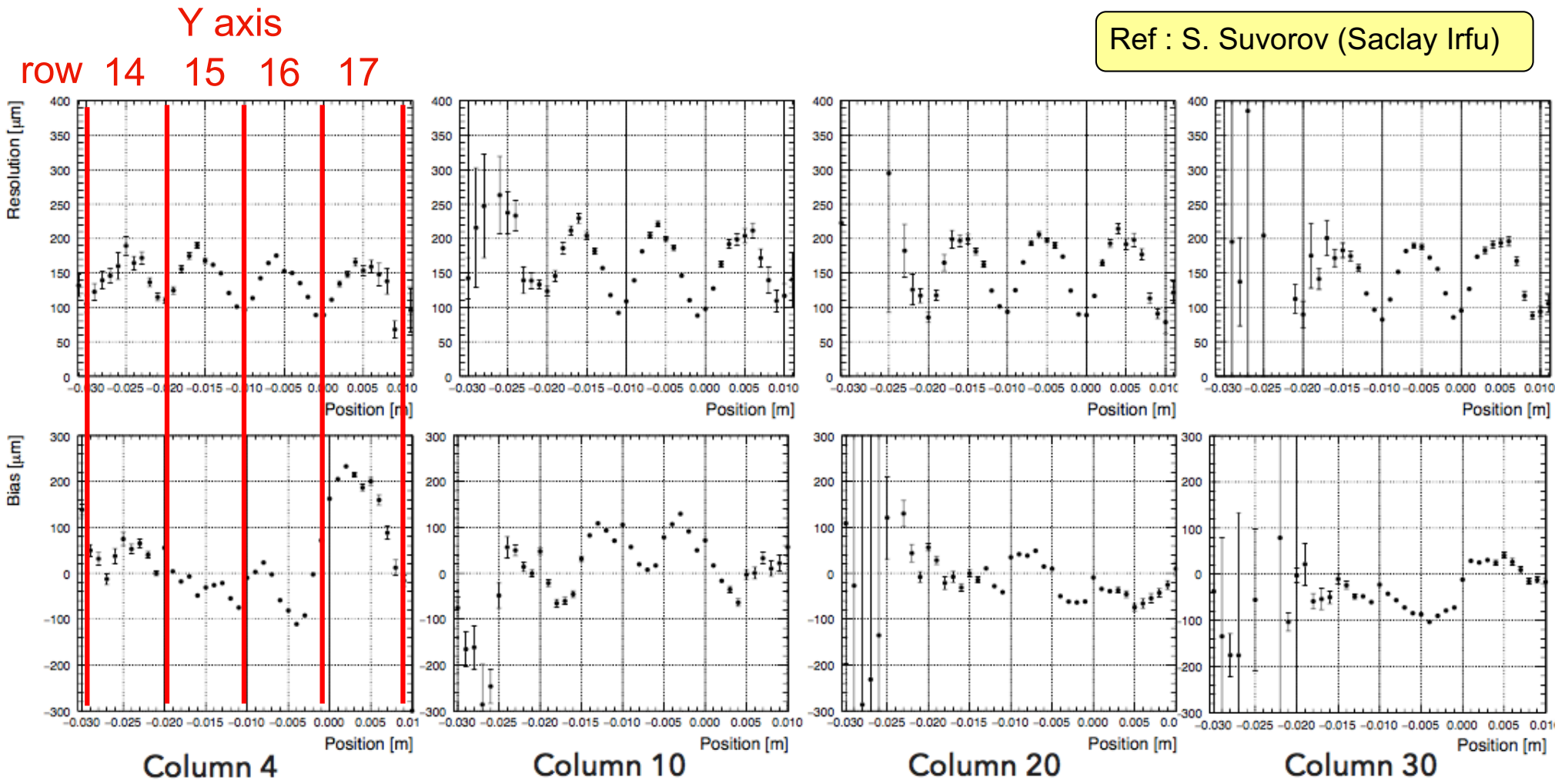


Peaking Time = 400 ns

Peaking Time = 612 ns



Ref : S. Suvorov (Saclay Irfu)

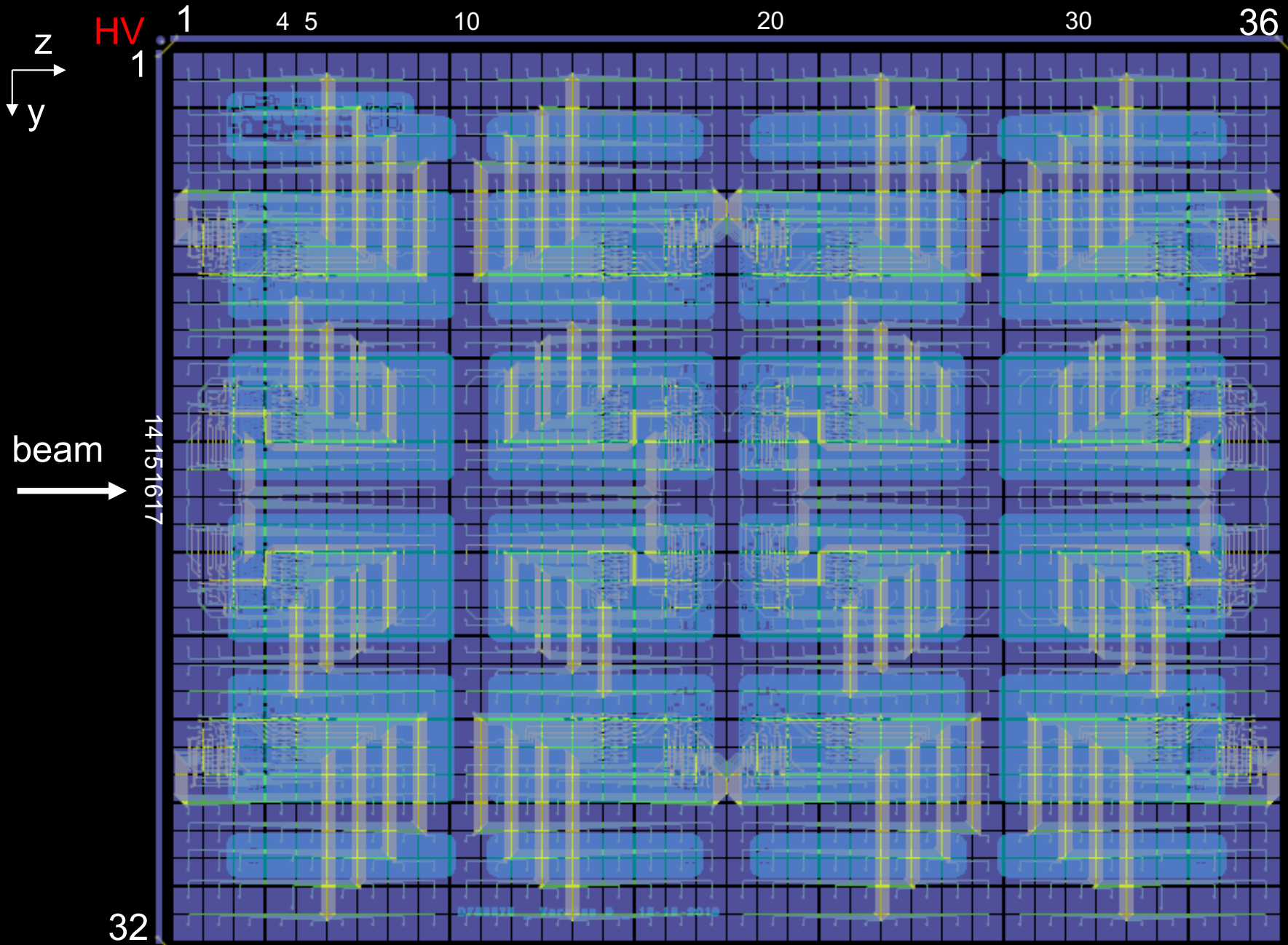


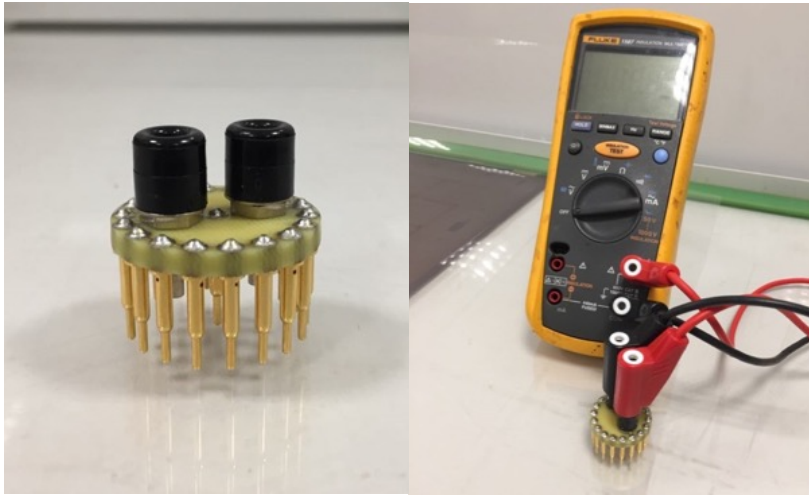
Column = z axis

The bias is still under investigations : may be due to large capacitance steps between neighbouring pads coming from the PCB layout (pad to connector layout) (measurements to be done)



# ERAM PCB DFS-2278 PAD-CONNECTOR LAYOUT





## CERN calibrated custom-made probe

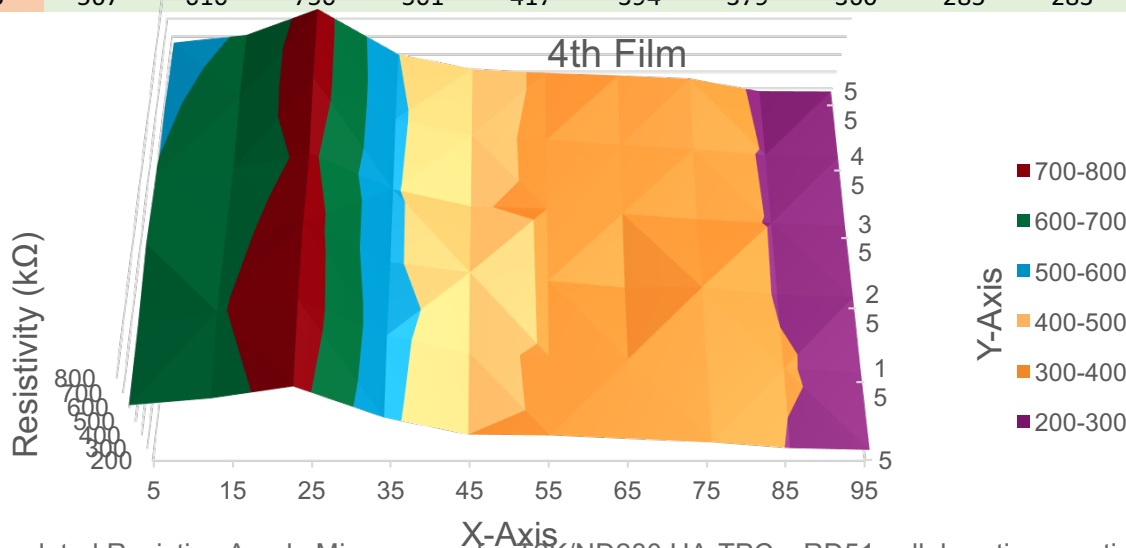
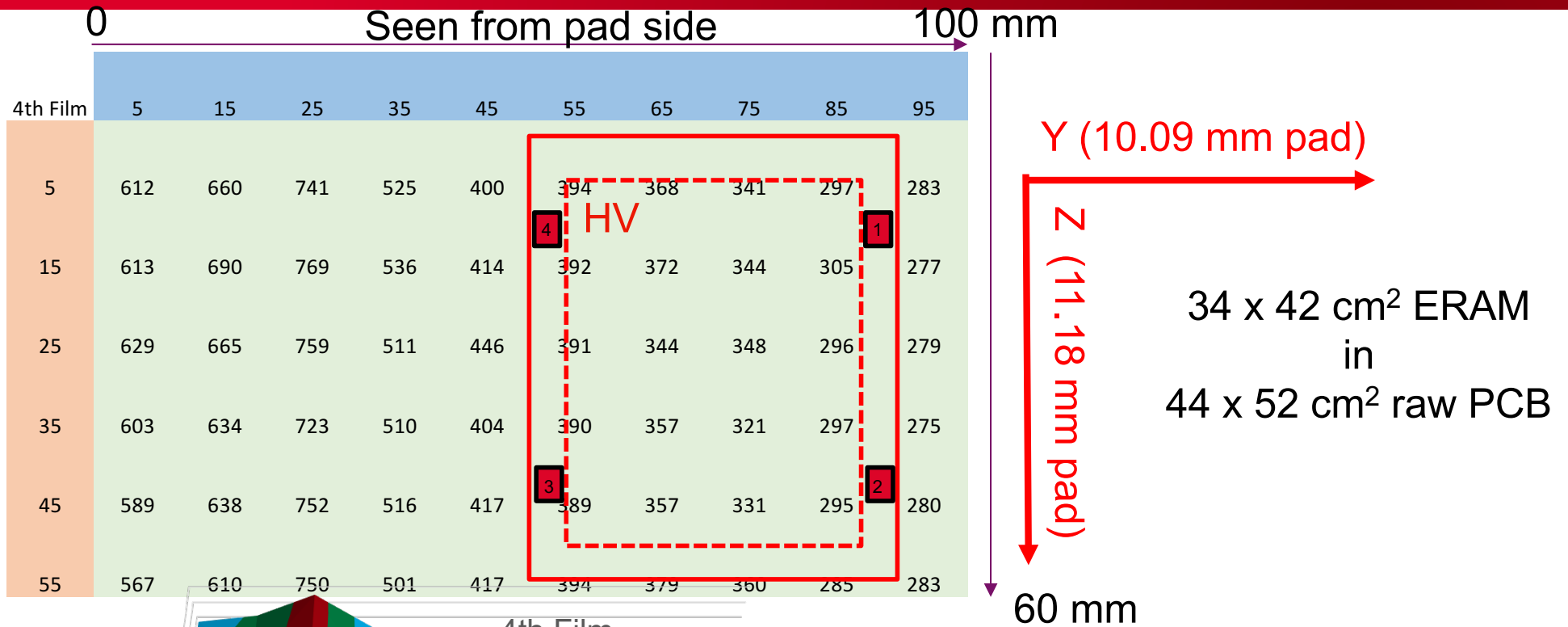
- Two rulers were adjusted to take surface resistivity measurement from 10cm x 10cm squares. The bottom-left corner of the film was assigned as origin point.



- By measuring the center of the squares, the film is scanned and results are transferred to Excel for 3D graph.

This new probe will be used for ERAM production

Ref: Elcin Akar (CERN/EP-DT-EF)



- Non-uniformity along Y due to sputtering process
- Very good uniformity in z (along neutrino beam)

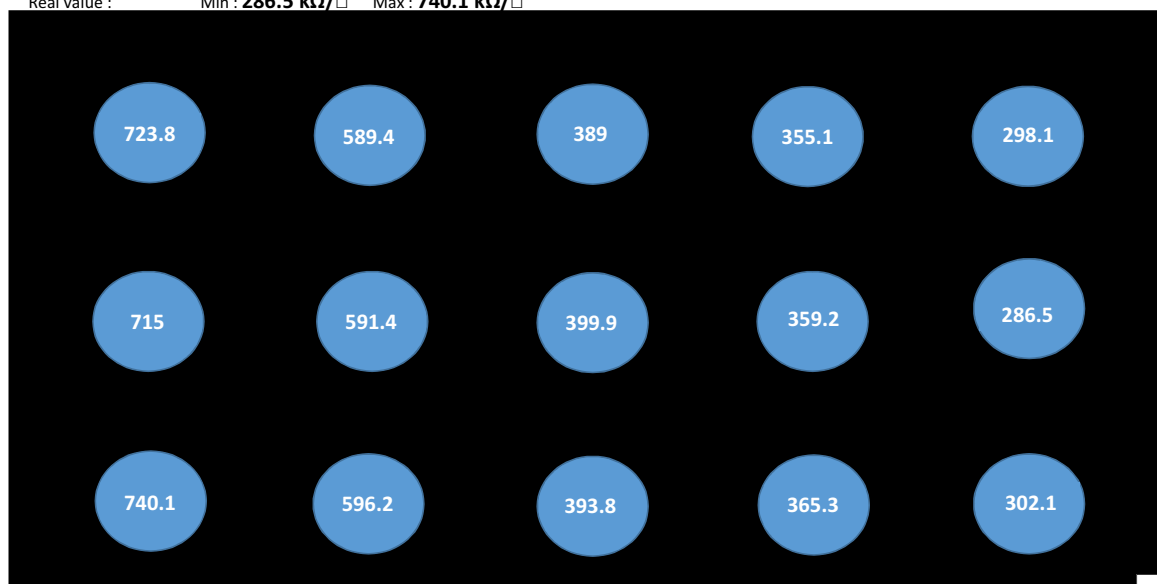
# Comparison of resistivity measurement for ERAM#01 DLC foil #4



## CERN Custom made probe

4th Film	5	15	25	35	45	55	65	75	85	95
5	612	660	741	525	400	394	368	341	297	283
15	613	690	769	536	414	392	372	344	305	277
25	629	665	759	511	446	391	344	348	296	279
35	603	634	723	510	404	390	357	321	297	275
45	589	638	752	516	417	389	357	331	295	280
55	567	610	750	501	417	394	379	360	285	283

Theoretical value **500 kΩ/□** CERN « Ochi » probe (2018) Foil size : 100x61cm  
 Real value : Min : **286.5 kΩ/□** Max : **740.1 kΩ/□**

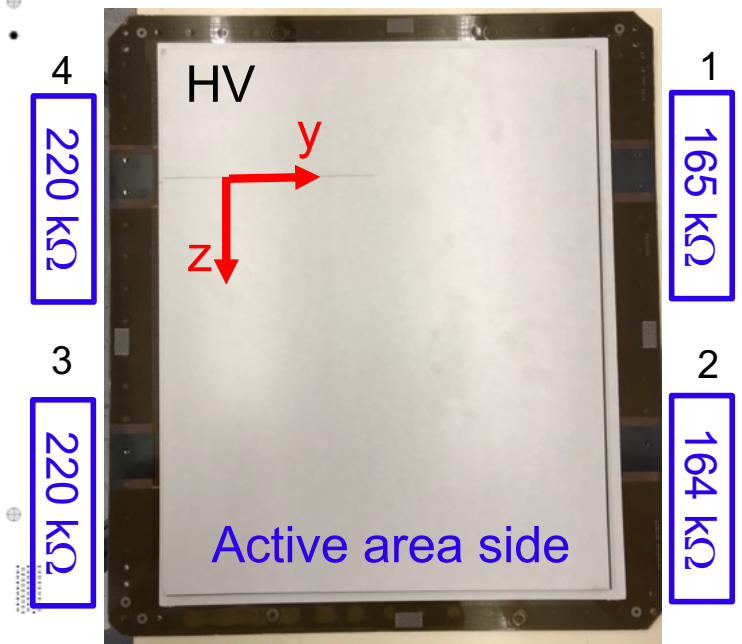
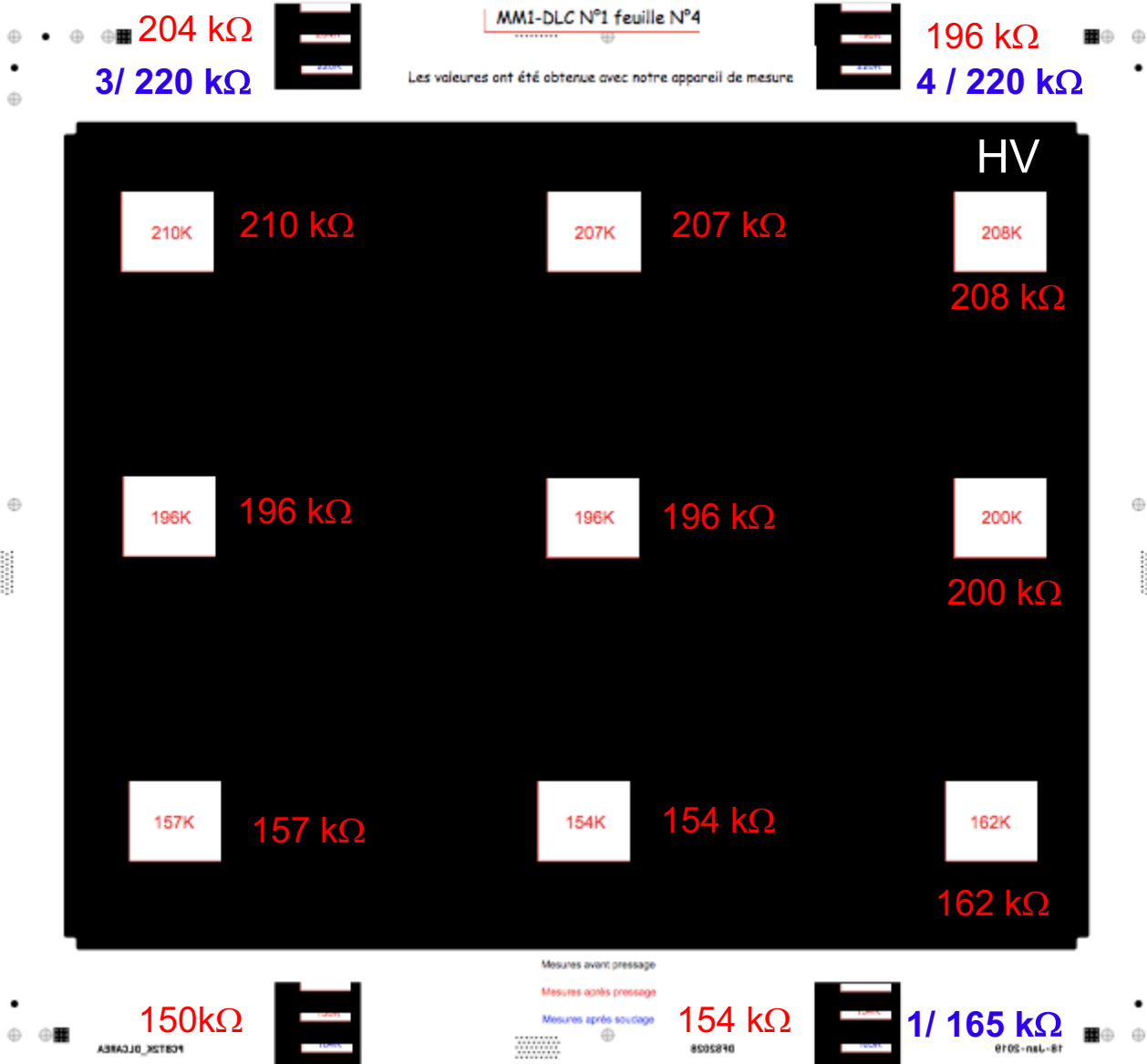


7-15 % difference  
 better reproductibility  
 with CERN probe  
 ~2-3 %



ERAM#1 (S/N 002) resistivity – active area side

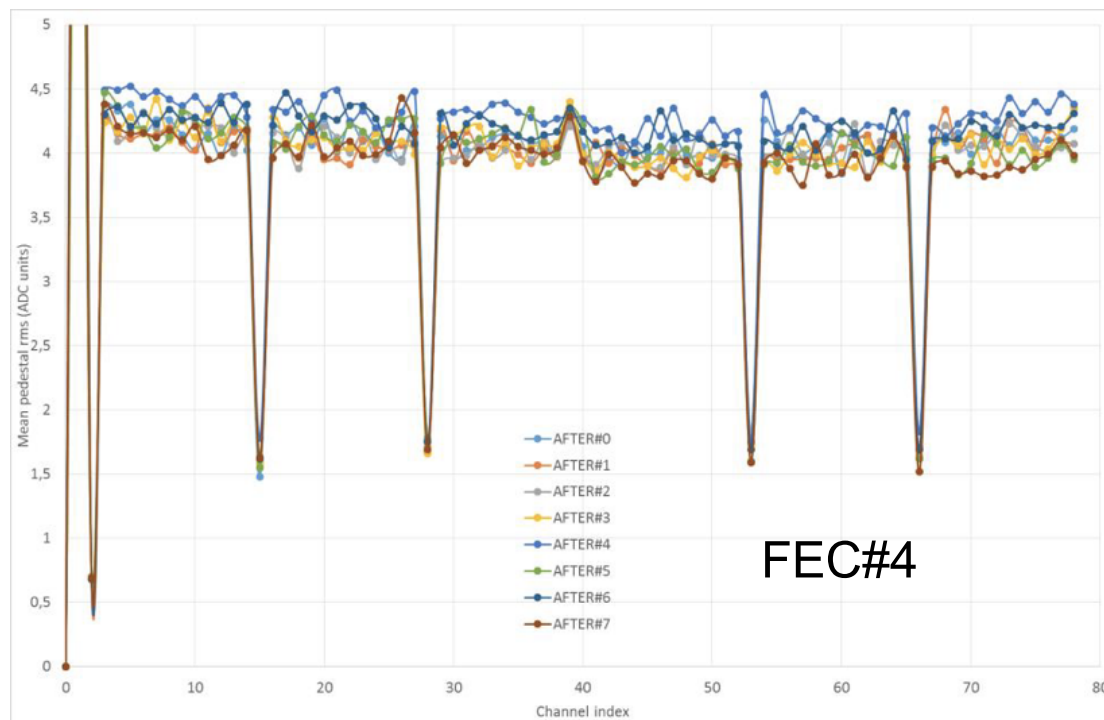
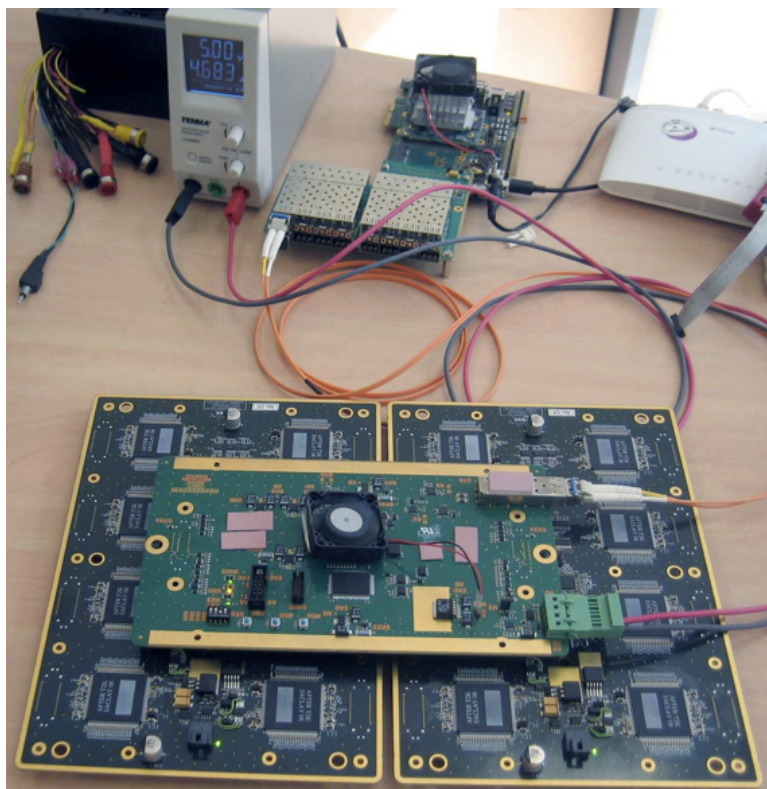
ERAM#1 (S/N 002)



Same ~60% drop as for MM1

Reminder for MM1-DLC1 & 2

- 1: 197 kOhm
- 2: 197 kOhm
- 3: 265 kOhm
- 4: 265 kOhm



120 fCrange; 116 ns peaking time; 25 MHz Fwrite

- 800 to 1200 e-rms of pedestal noise seen in average for the 72 channels of each chip  
Still some debug needed (card shielding, power of FEC through the FEM unstabilities, ..)

But these first card prototypes are a very robust design which validates the technical choices

including its coupling to the detector .....

Ref : D. Calvet (Saclay Irfu)  
J-M Parraud (LpnHe)



### Noise issues

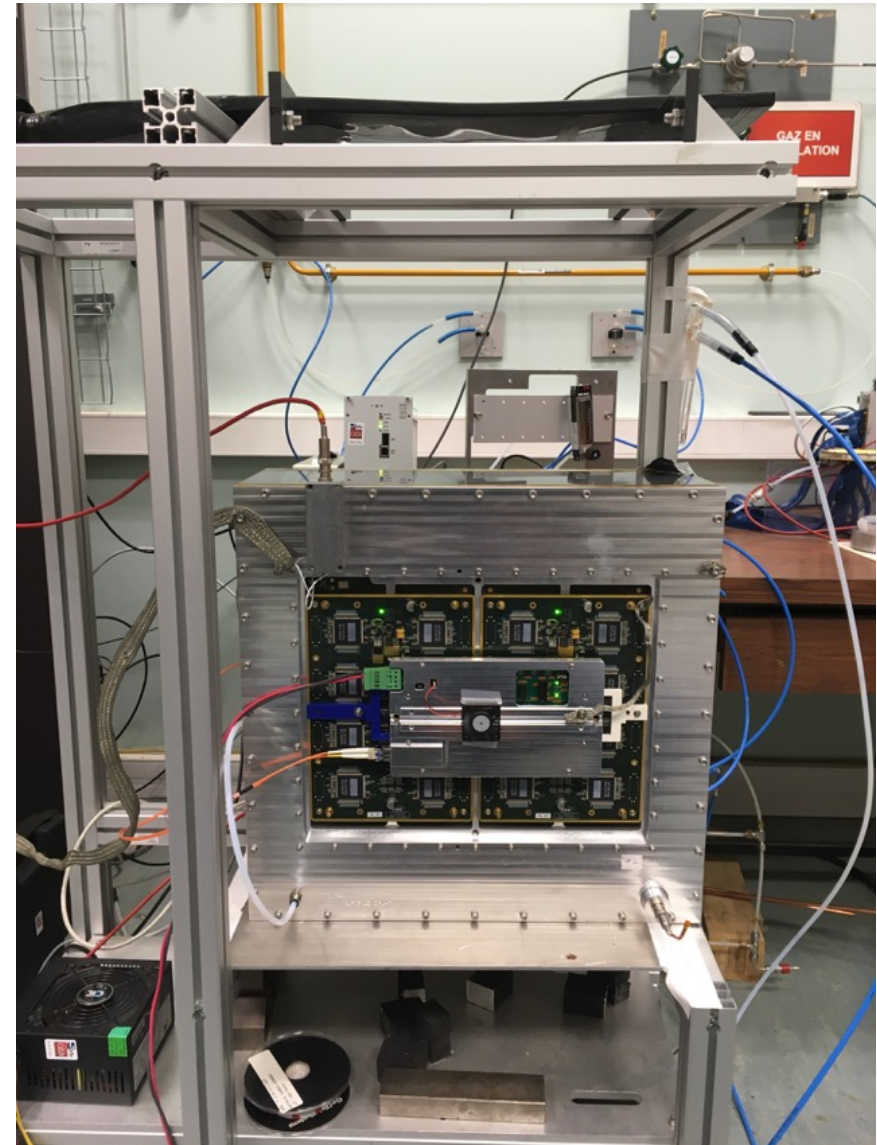
- Identification of floating ground (FEM/FEC):  
rms~17-20 ADC after correction (> 100 ADC before)
- Using an external RCR HV filter, noise was lowered  
to the usual 7-8 ADC rms
- → GND or shielding problem with on-board HV filter

ERAM active area (mesh@ GND)



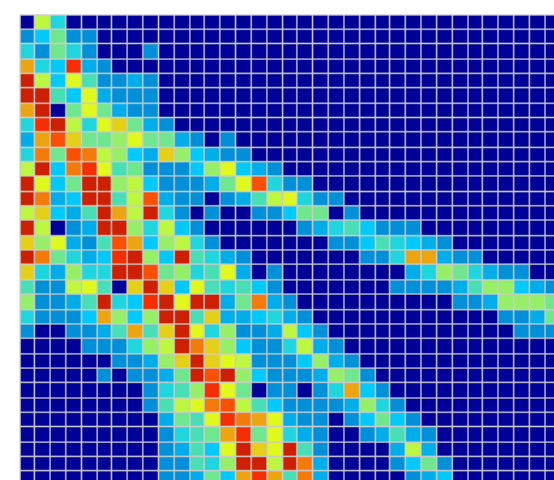
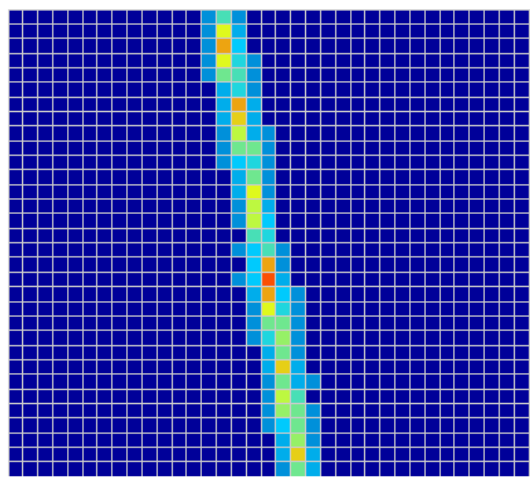
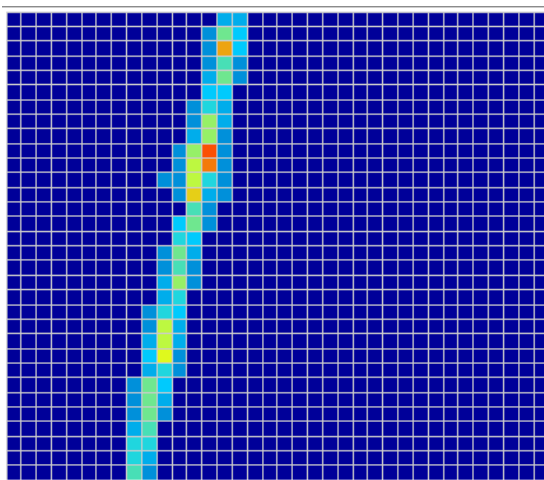
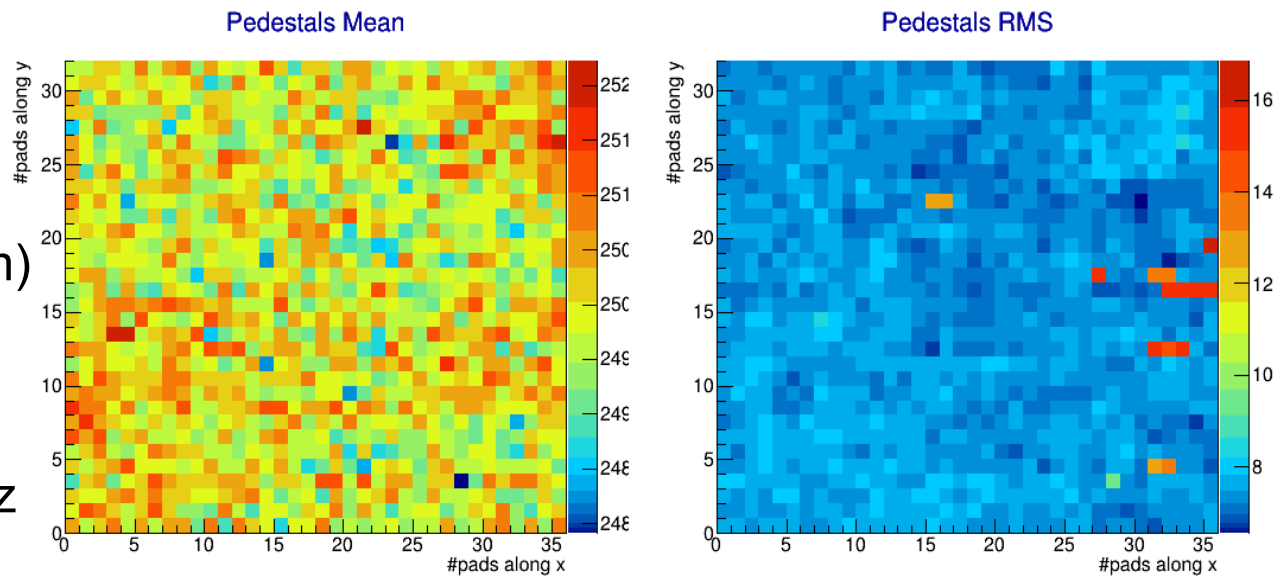
Guard Frame PCB @ ground

### Experimental setup



### Experimental setup

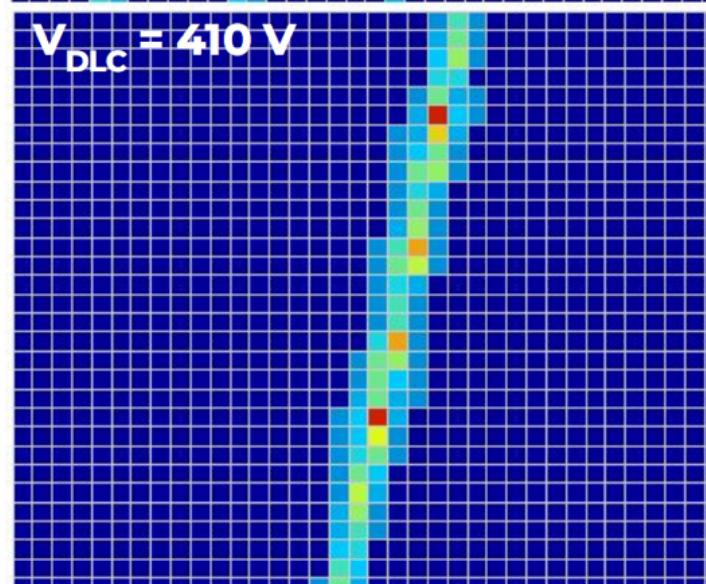
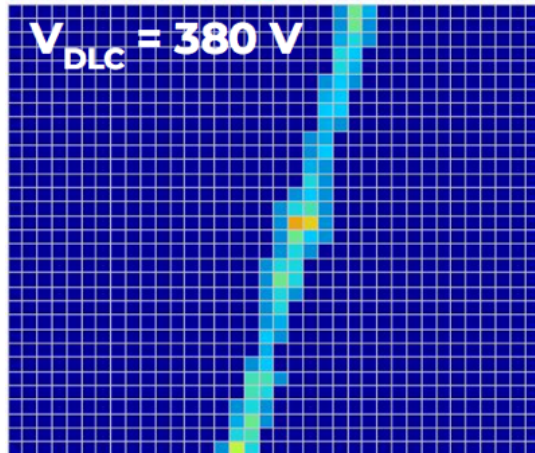
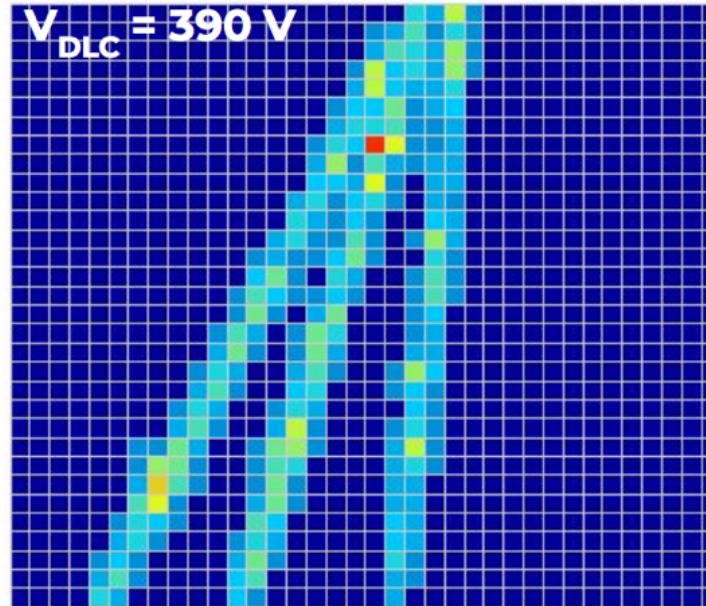
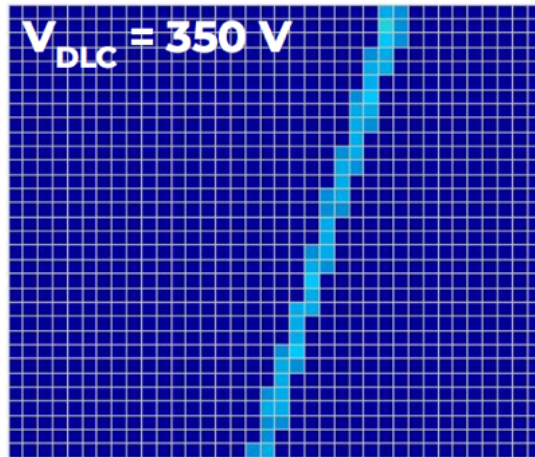
- Zero-suppressed data
- Ddrift = 15 cm
- $V_{\text{cathode}} = -4207 \text{ V}$  (280 V/cm)
- $V_{\text{DLC}} = 380 \text{ V}$
- Peaking time: 220 ns
- Sampling frequency: 25 MHz
- Trigger rate  $\sim 0.6 \text{ Hz}$



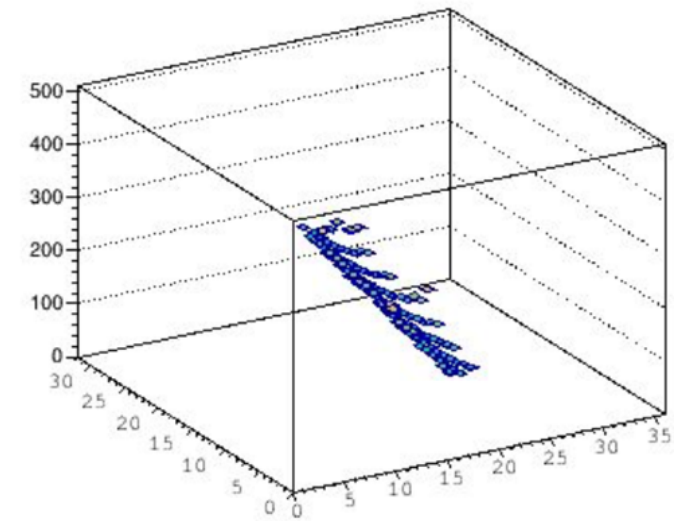
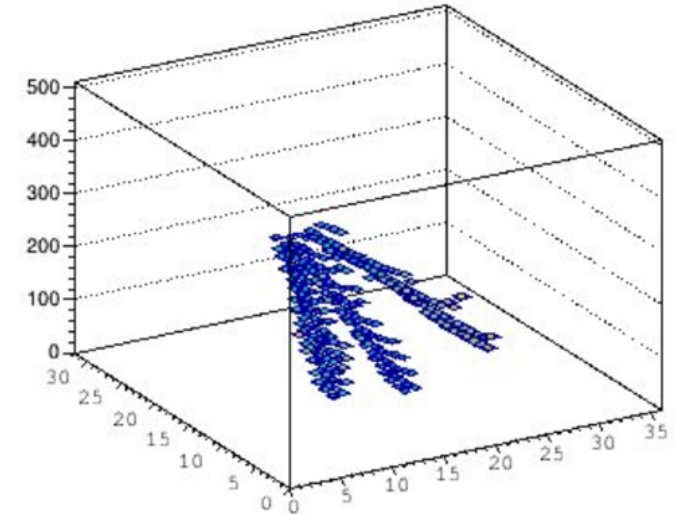
Ref : D. Attié / M. Lehuraux (Saclay Irfu)



Ref : M. Lehuraux (Saclay Irfu)



Peaking time = 200 ns



Larger charge spreading to be confirmed, but less effective charge collection (thicker glue)

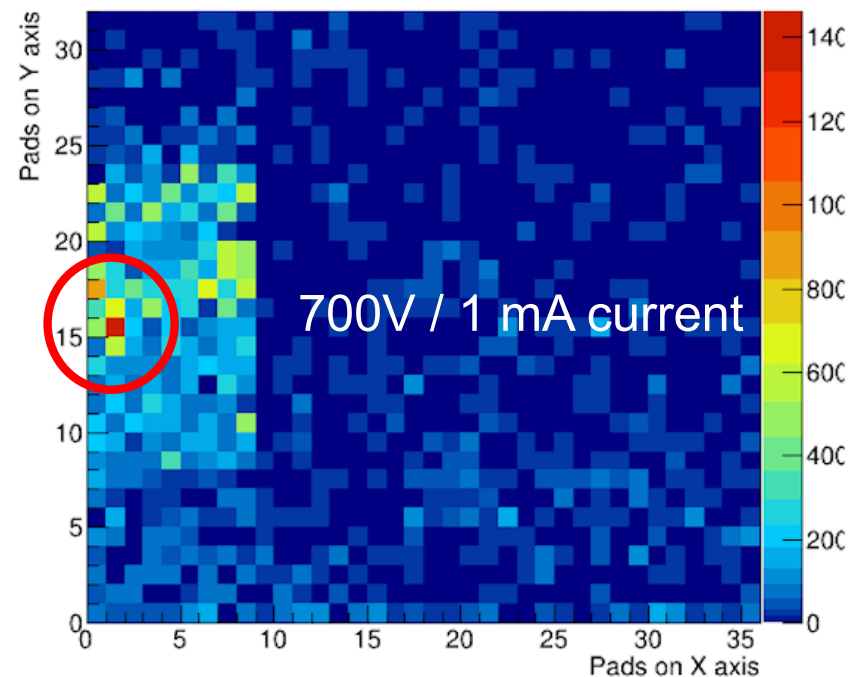
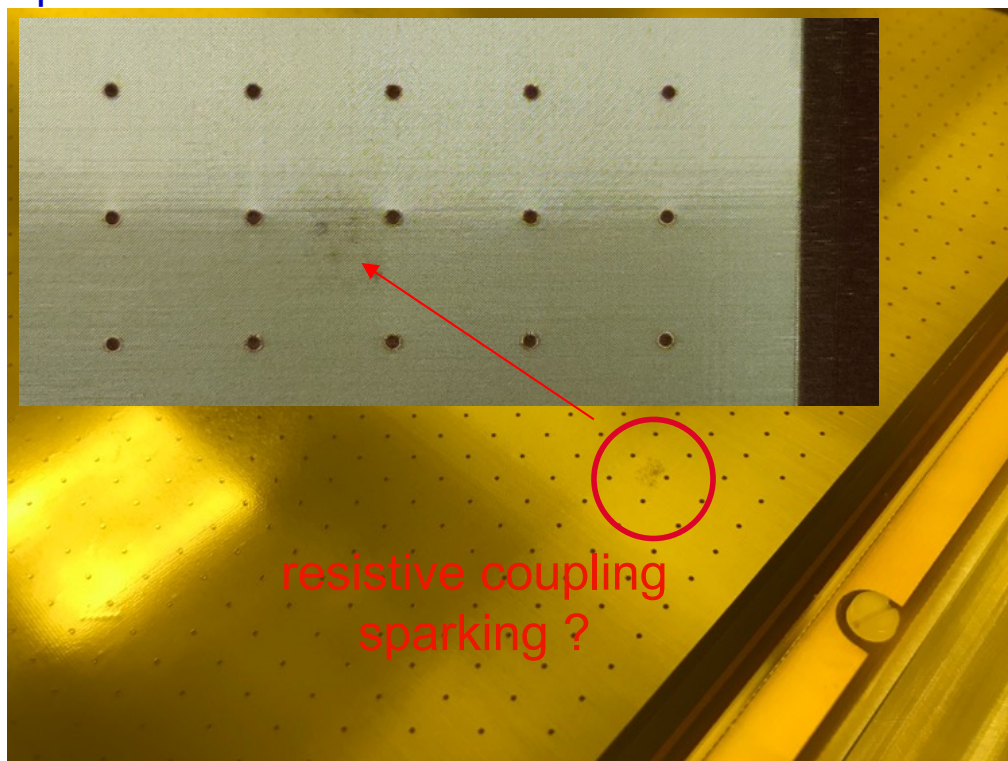


After 2 days of operation current fluctuations occurred followed by a permanent ~400 kOhm DLC-mesh short

- A “Dark” zone was identified.
  - Solved with washing using soap, rinsing with deionized pressurized water & drying @ 50 °C during 5h
- But reappeared after 3 more days ...
- Probably due to dust released when the melamine protection was removed in clean room



Occupation





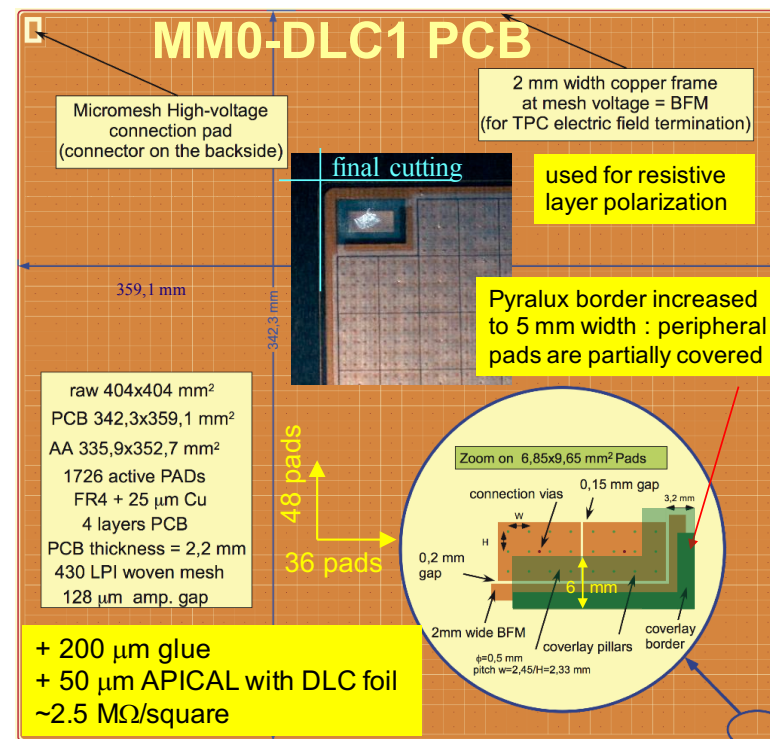
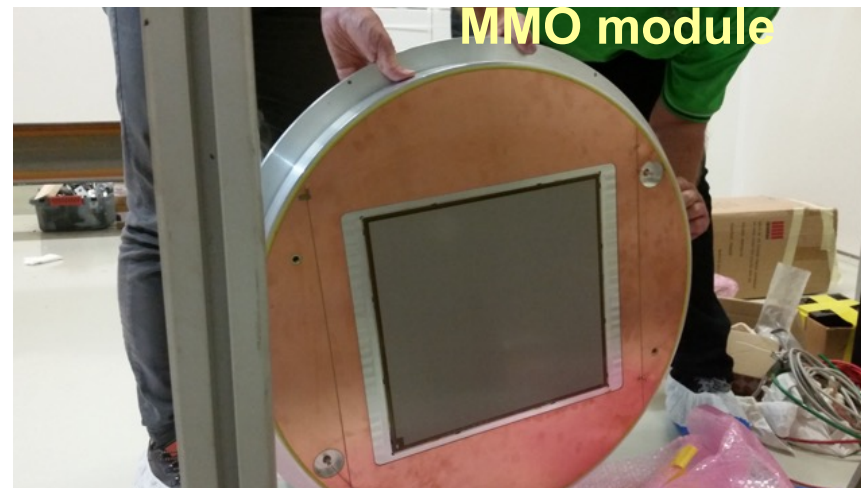
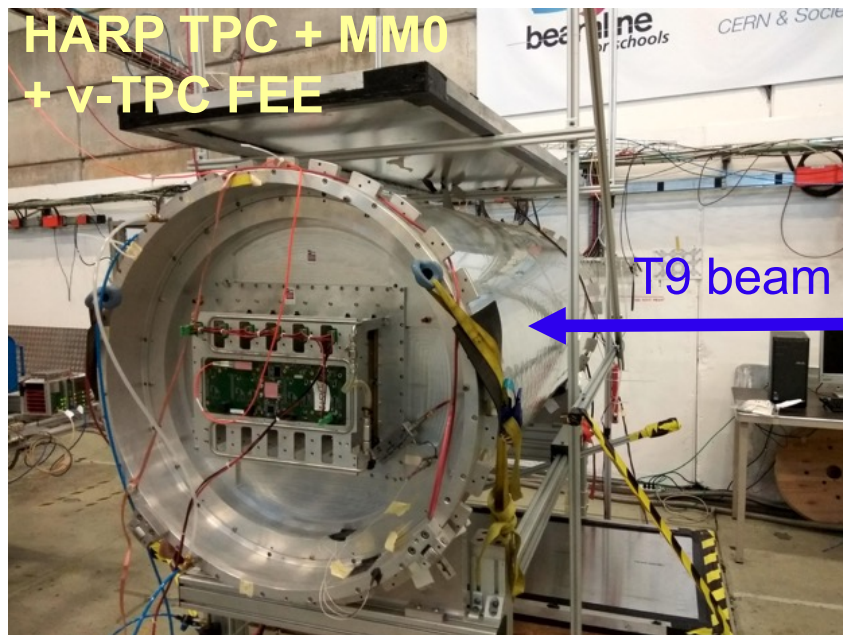
- The resistive anode Micromegas technology will be used for the new HA-TPCs of the T2K Near Detector upgrade.
- The ERAM design is close to be ready for production. Data analysis of test beams of prototypes and modelization of the signal waveforms are on-going to fix the DLC foil resistivity and the RC of the structure. The sensitivity of the detector performances on the RC non-uniformities also needs to be characterized.
- DLC resistivity seems under control for the ERAM production stage at CERN (DLC foil pressing & wave soldering) but the required tolerances on the DLC foils resistivity needs to be discussed & fixed with the manufacturer.
- HA-TPCs are planned to be installed in ND280 in summer 2022. We are on the path to start the production of 32 ERAM modules at CERN and the corresponding FEE cards for 40k ch. at the end of this year after a test beam at DESY.

DE LA RECHERCHE À L'INDUSTRIE

cea **BACKUP**







## Gas volume : HARP TPC

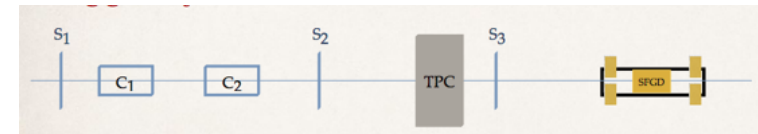
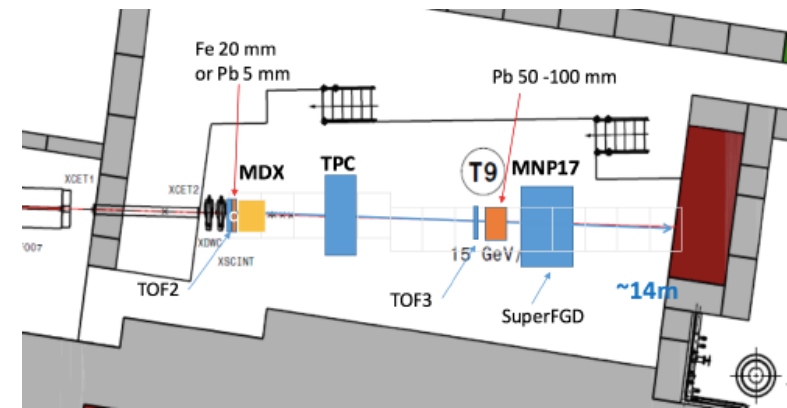
- 1.5 m drift distance / 25 kV (166 kV/cm)
- 25 l/h Argon(95%)/CF4(3%)/isobutane(2%)

## Detector : MM0 module

- Micromegas module MM0 with 2.5 MΩ/■ DLC
- horiz. x vert. = 36 x 48 pads
- each pad 0.97 x 0.69 cm
- nominal MM voltage 340 V (up to 380 V)
- V-TPC FEE: Sampling time 80 ns (12.5 MHz)
- nominal peaking time 600 ns

## Data taking

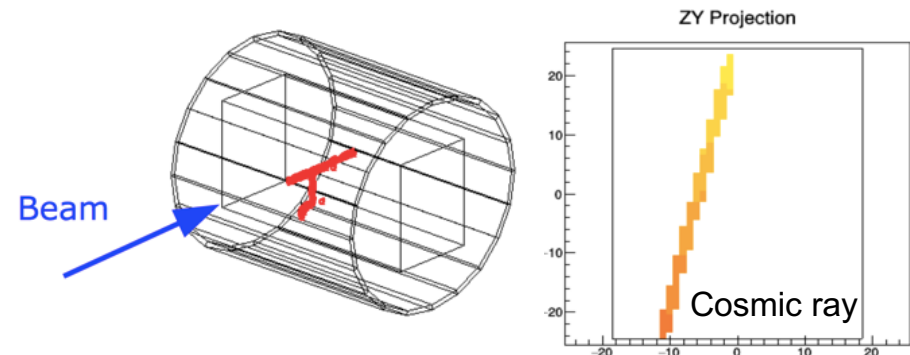
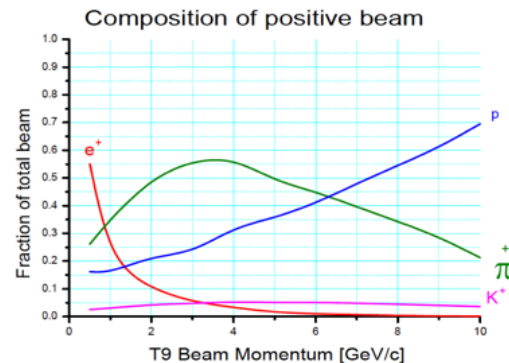
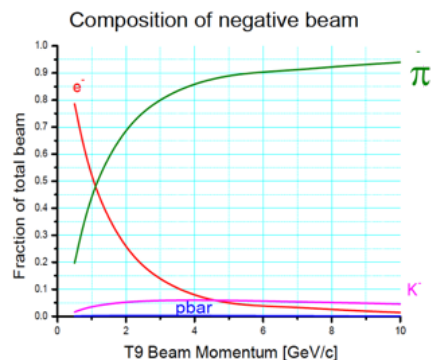
- Cosmic trigger with 2 plastic scintillators +MPPC
- Fe55 source for 5.9 keV X-rays
- Beam : 0.5, ± 0.8, 1, 2 GeV/c momentum



$\pi, e, p$  trigger

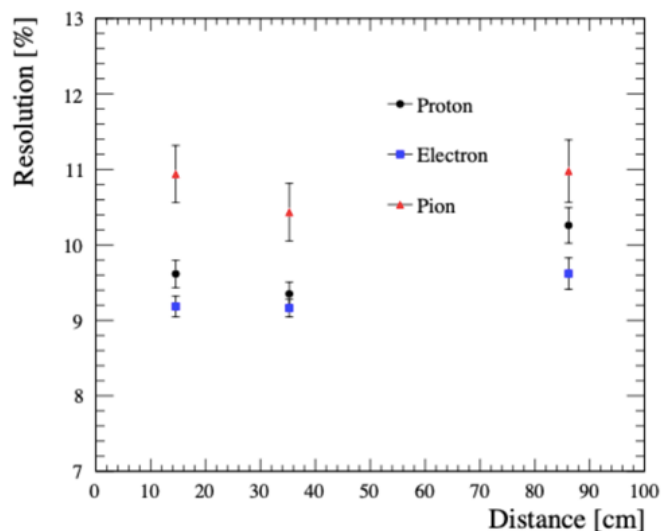
Particle	Selection
Electrons	Scintillators + Cherenkov
Protons (+Kaons)	S1(delayed) * S2 (delay proton TOF between S1 and S2)
Pions (+ muons)	Scintillators * protons * electrons
Cosmic ray	from the scintillators panels (only out of spill)

+  $^{55}\text{Fe}$  X-ray source in the middle of the cathode

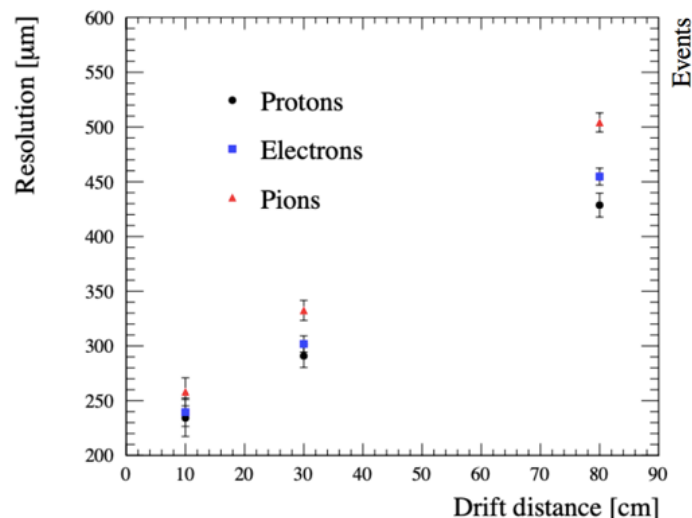




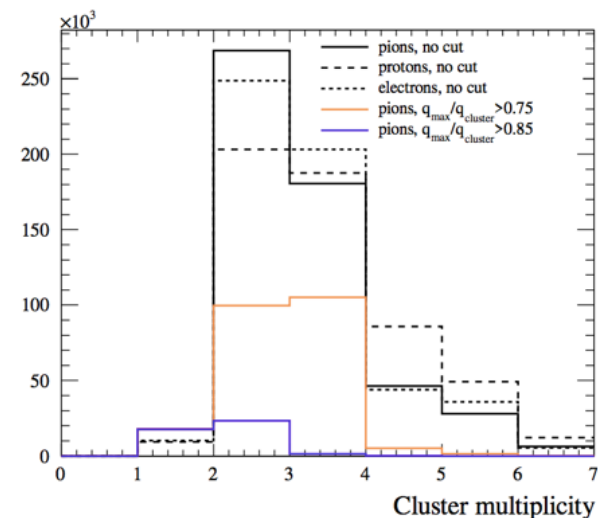
D. Attié et al., Nucl Instrum Meth A 957 (july 2019) DOI: [10.1016/j.nima.2019.163286](https://doi.org/10.1016/j.nima.2019.163286)



7% for 2 modules track length  
<10% requirement



~ 2 times better ~320  $\mu\text{m}$   
@ 30 cm than non-resistive  
 $\nu$ -TPC modules (~600  $\mu\text{m}$ )



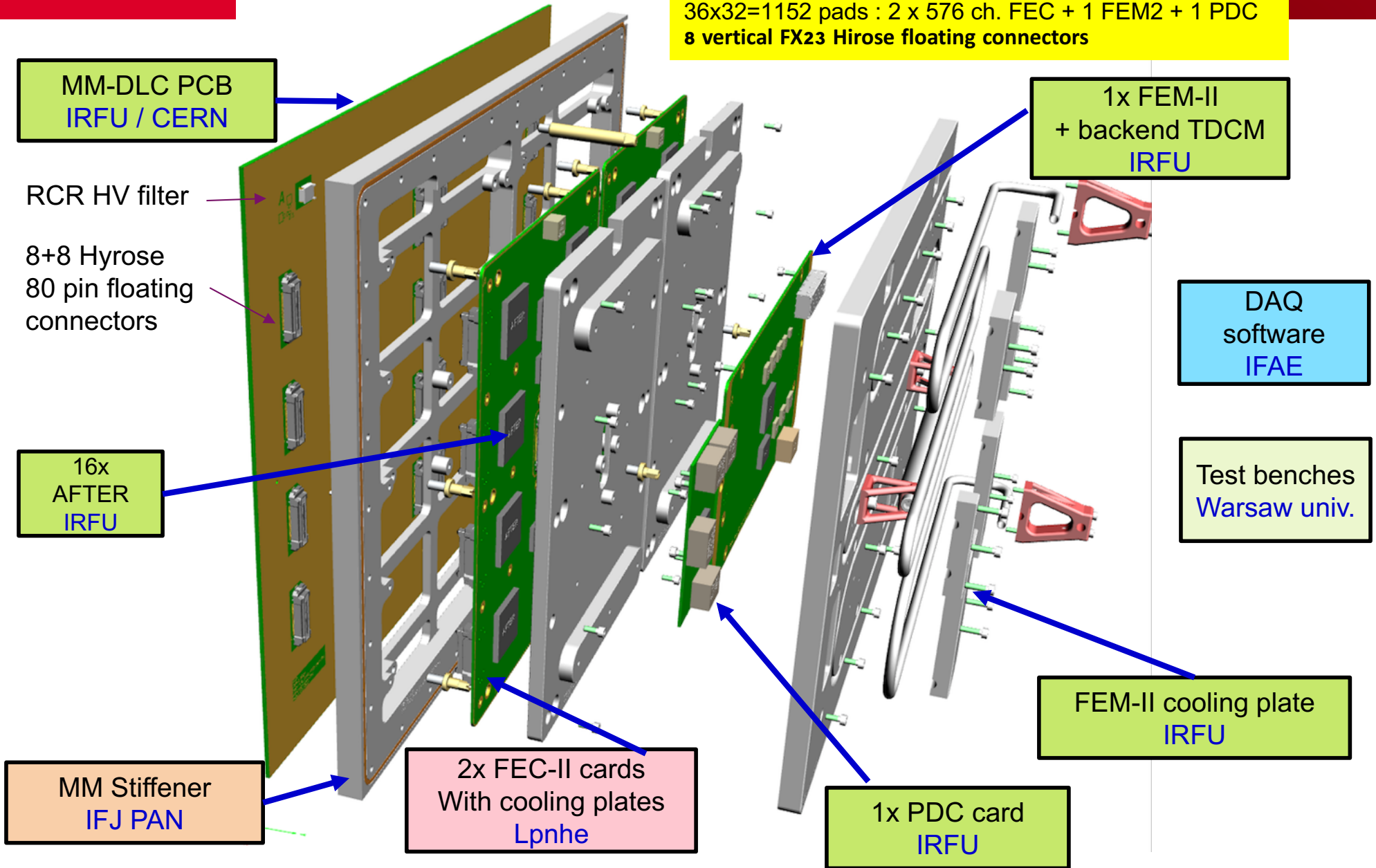
Multiplicity of 2-3  
(for 600 ns shaping time)

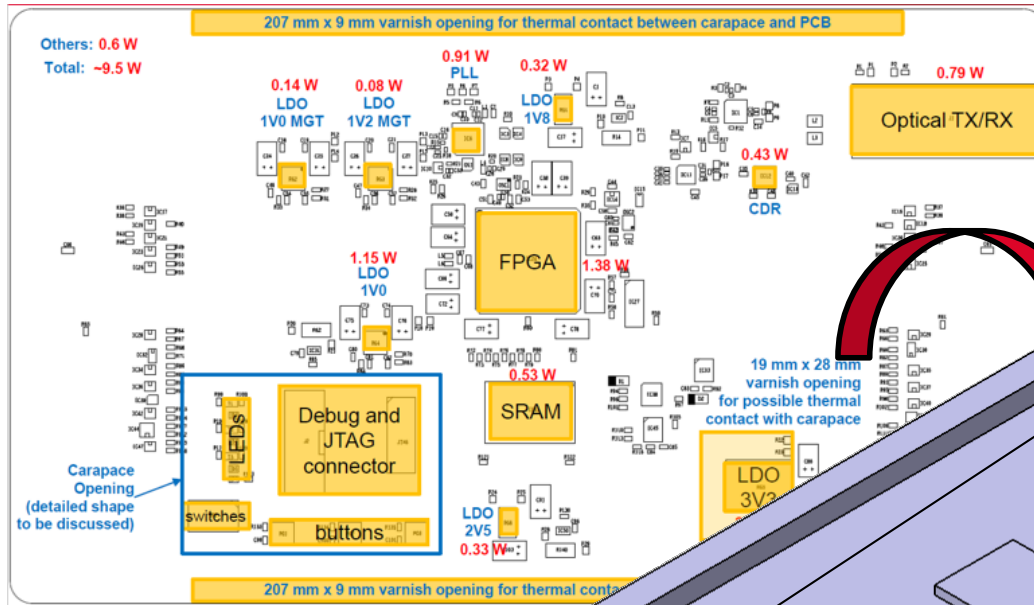
- Next step : lower the number of electronics channels with full size ERAM module
- Increase charge spreading for final ERAM segmentation (~10x11 mm<sup>2</sup> pads)

# cea The ERAM module



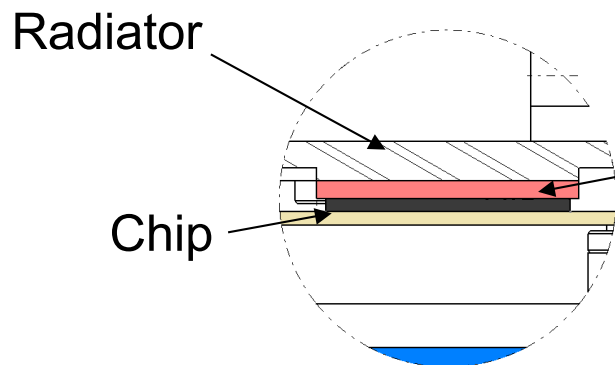
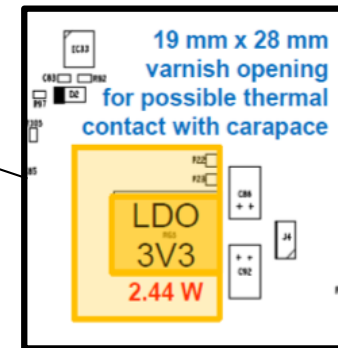
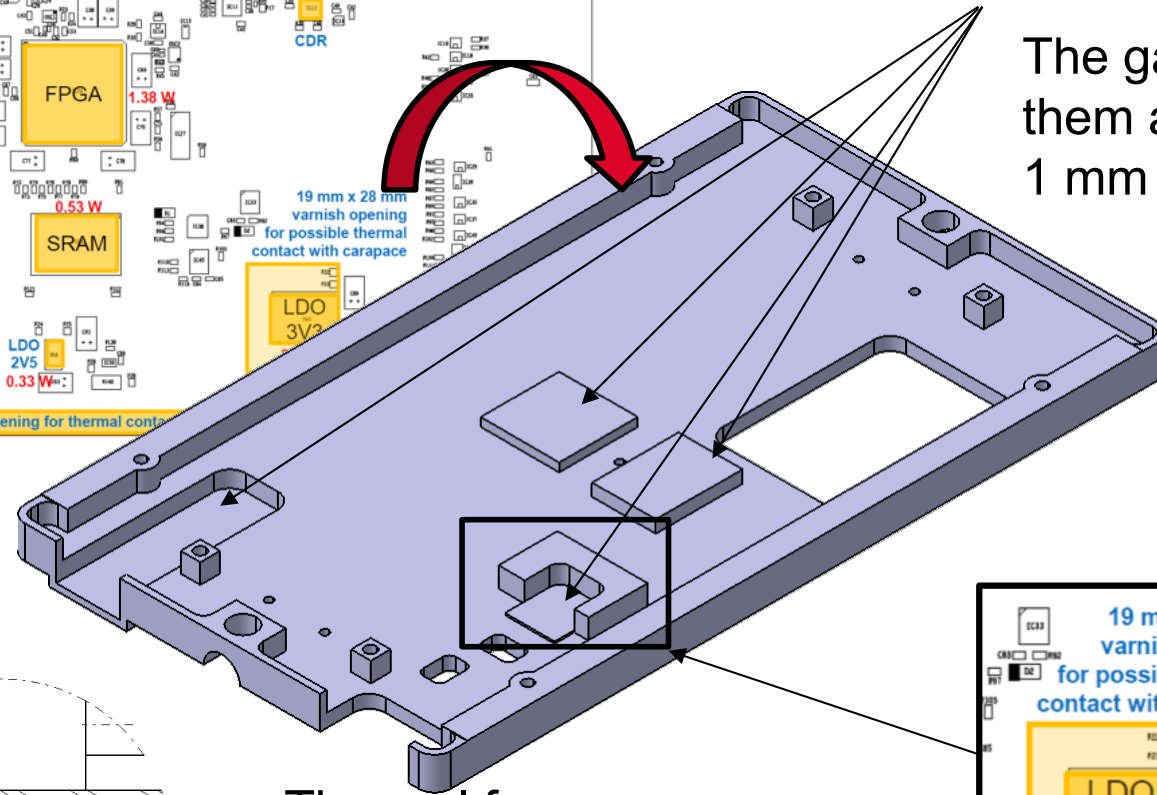
36x32=1152 pads : 2 x 576 ch. FEC + 1 FEM2 + 1 PDC  
8 vertical FX23 Hirose floating connectors





Cooling of FPGA, SRAM, LDO 3V3 and Optical TX/RX

The gap between them and the chips is 1 mm

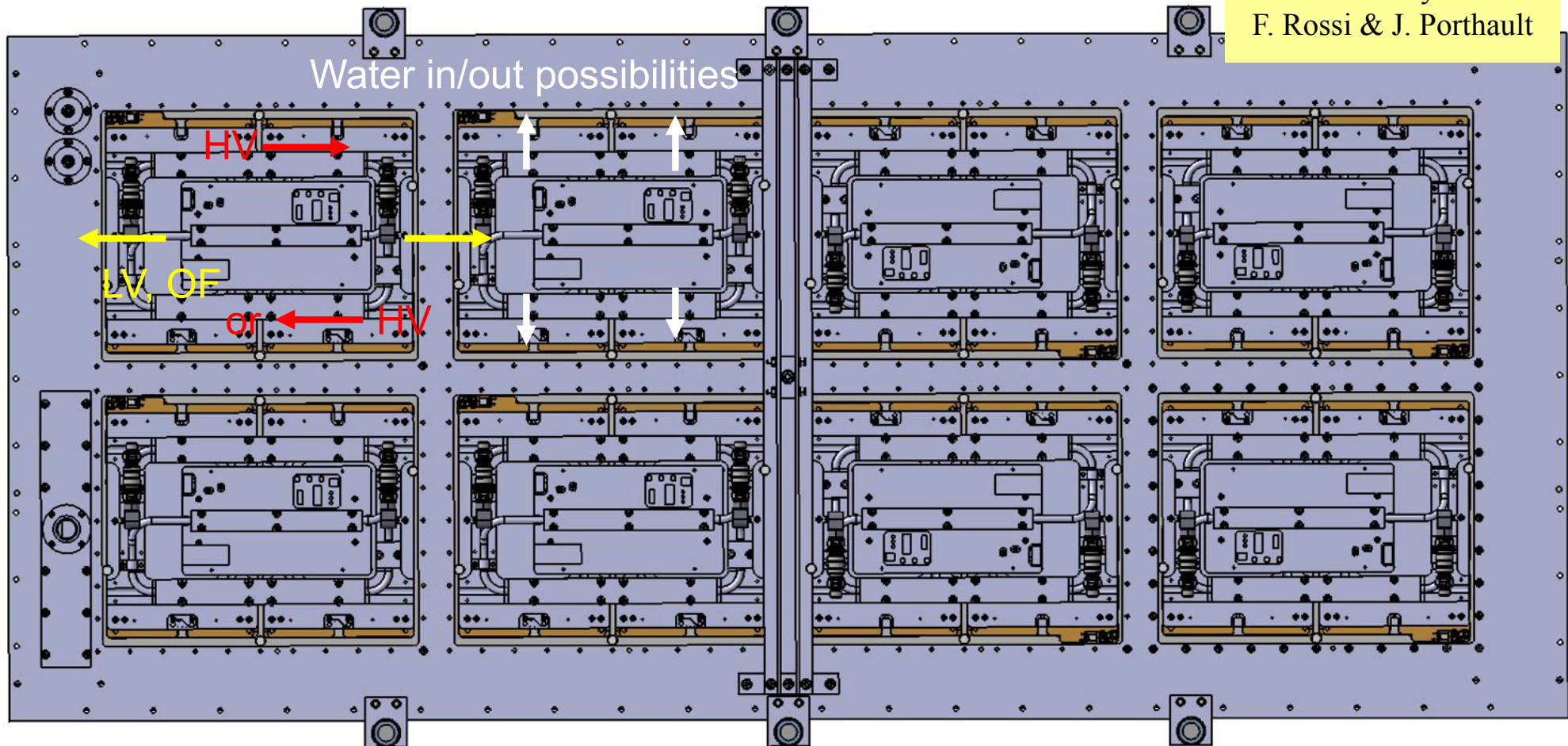


Ref: J. Porthaul/F. Rossi (Ifu)



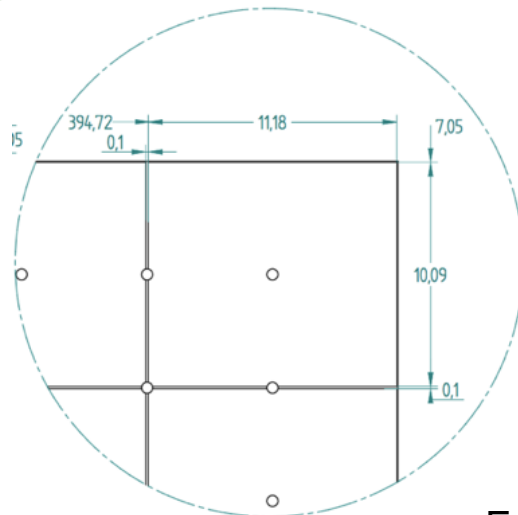
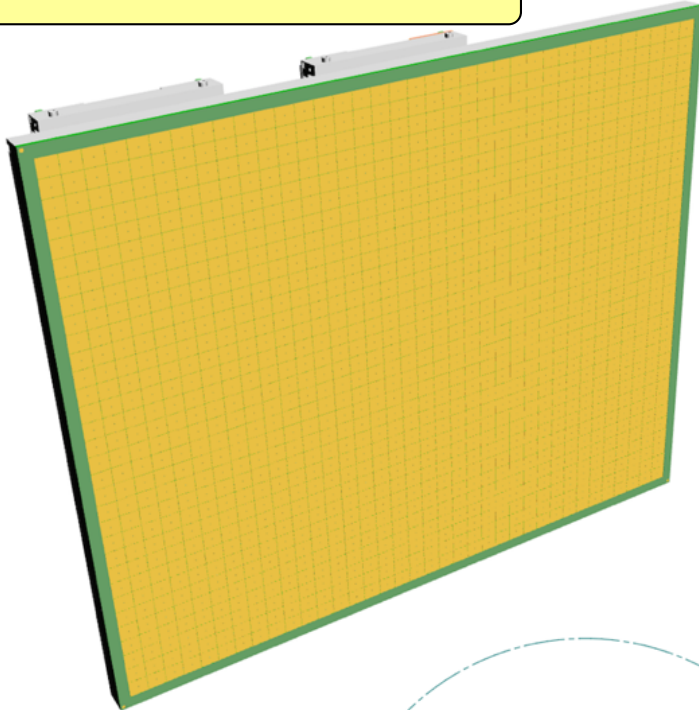
- MF dimensions : 820 mm x 1865 mm
- cooling pipes connectors, cooling pipes path, HV and LW cables paths to be defined & fixed
- Cooling pipes paths to be fixed in order to fix connectors orientation on ERAM
- Symmetries : ERAM can be flipped 180° on MF

Ref: H. Przybilski  
F. Rossi & J. Porthault





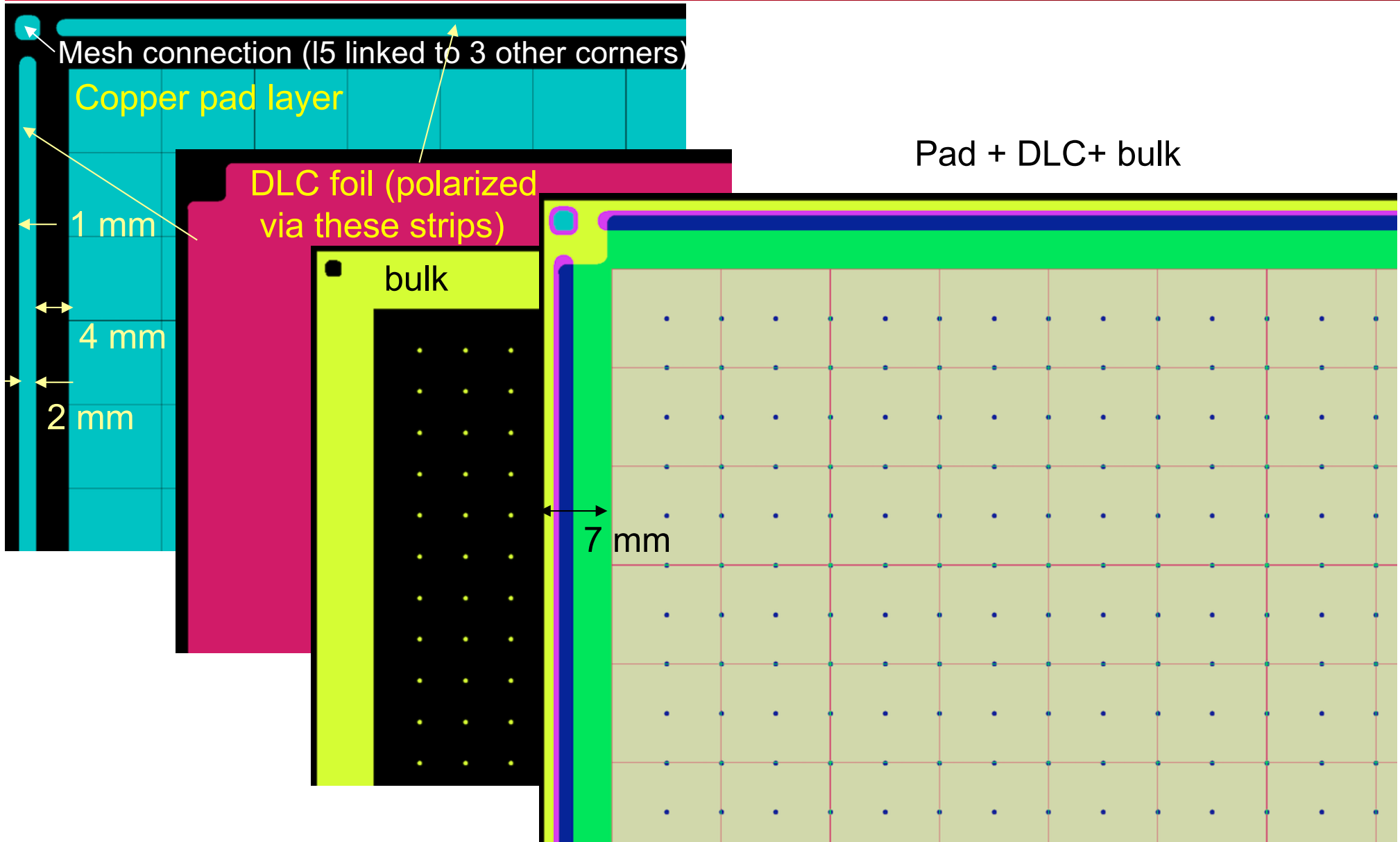
ref: CERN/IRFU – DFS2278



## 6 Couches

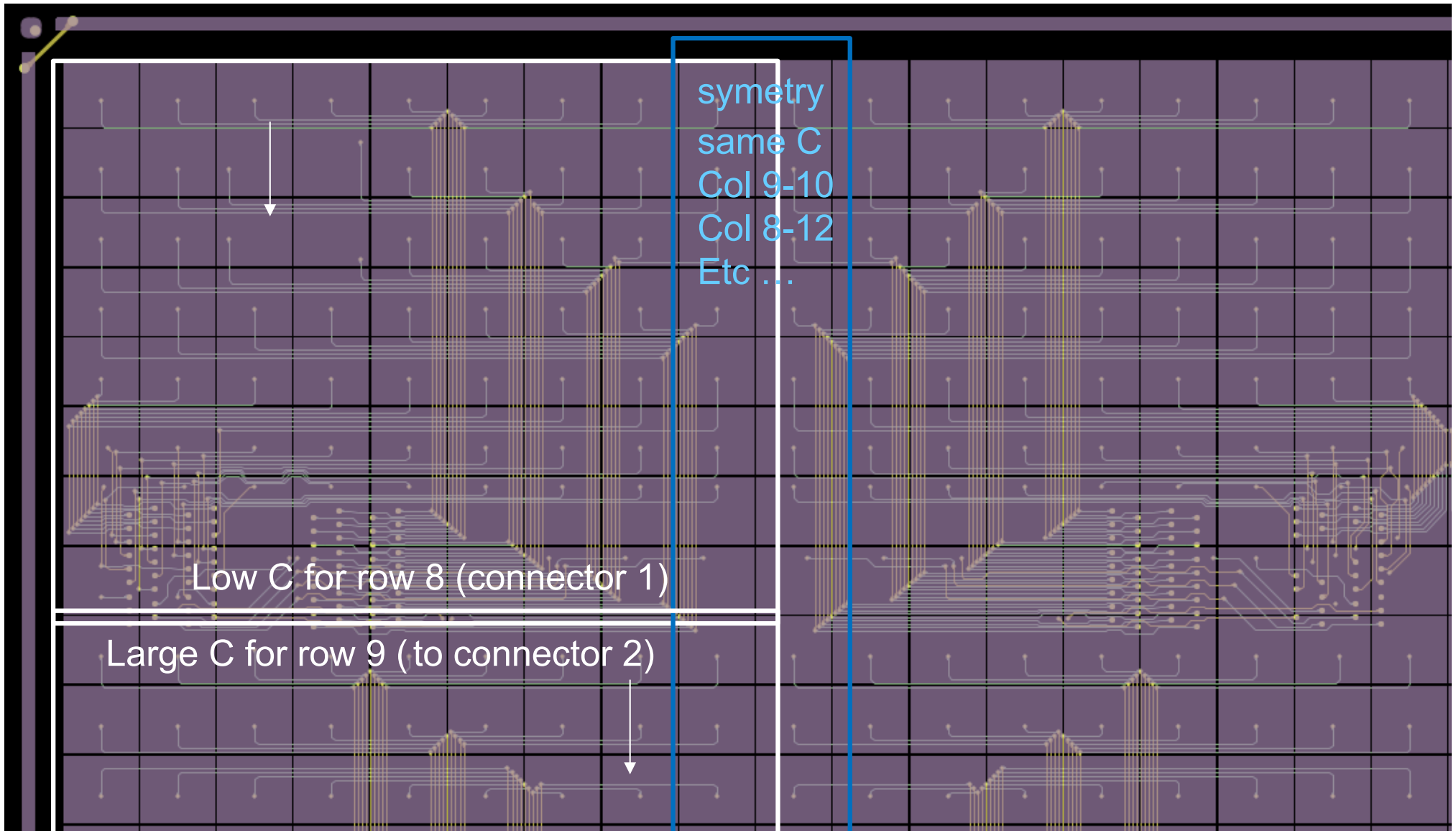
CLASSE		5	Ep. TOTALE		2.4
<b>EMPILAGE</b>		<b>Nom</b>			
		TOP-BOT => 2.2mm +0.2/-0			
etm	Solder mask	SPRAY 30 µm			
	Finition	NiAu			Ep. Ni 0.005
ltop	Feuillard Cu	9	35		
	Type de colle	pregreg	3x125	Ep. 0.375	
L2	Feuillard Cu	9	35		
	Type de colle	pregreg	3x125	Ep. 0.375	
L3	Cuivre de base	35			
	Matière	EPOXY			Ep. 1
L4	Cuivre de base	35			
	Type de colle	pregreg	3x125	Ep. 0.375	
L5	feuillard cu	9	35		
	Type de colle	pregreg	3x125	Ep. 0.375	
lbot	feuillard cu	9	35		
	Type de colle	pregreg	125 ss fibre	Ep. 0	
	Type de colle	pregreg	1x75	Ep. 0.075	
	Matière	APICAL NP			Epaisseur 0.05
DLC	DLC	500-600 K ohm + ligne AG			
BULK	Coverlay	BULK gap 128µ mesh 45/18			
<b>DÉBIT MATIÈRE</b>		P6:508x457	<b>TAILLE FINALE</b>		420 x 340

Epoxy (~0,02 mm) is used to fill the gap between copper pads



# EXAMPLE OF CAPACITANCE STEPS DUE TO THE PAD-CONNECTOR LAYOUT

Largest C steps between two connectors with no layout symmetry

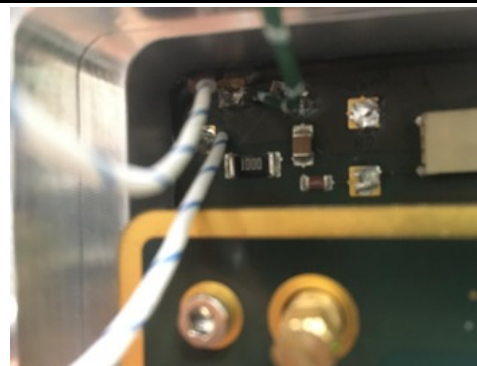
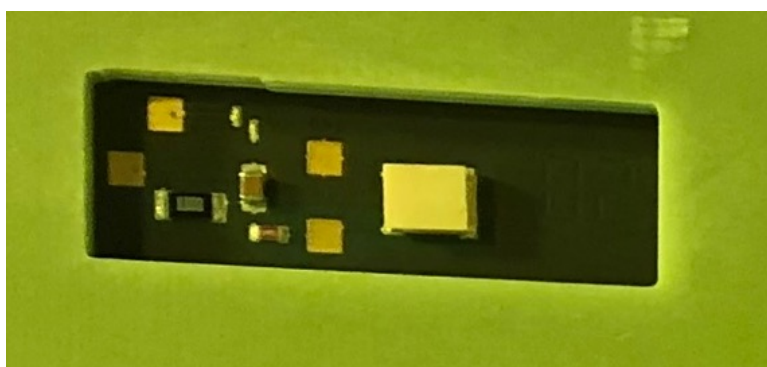
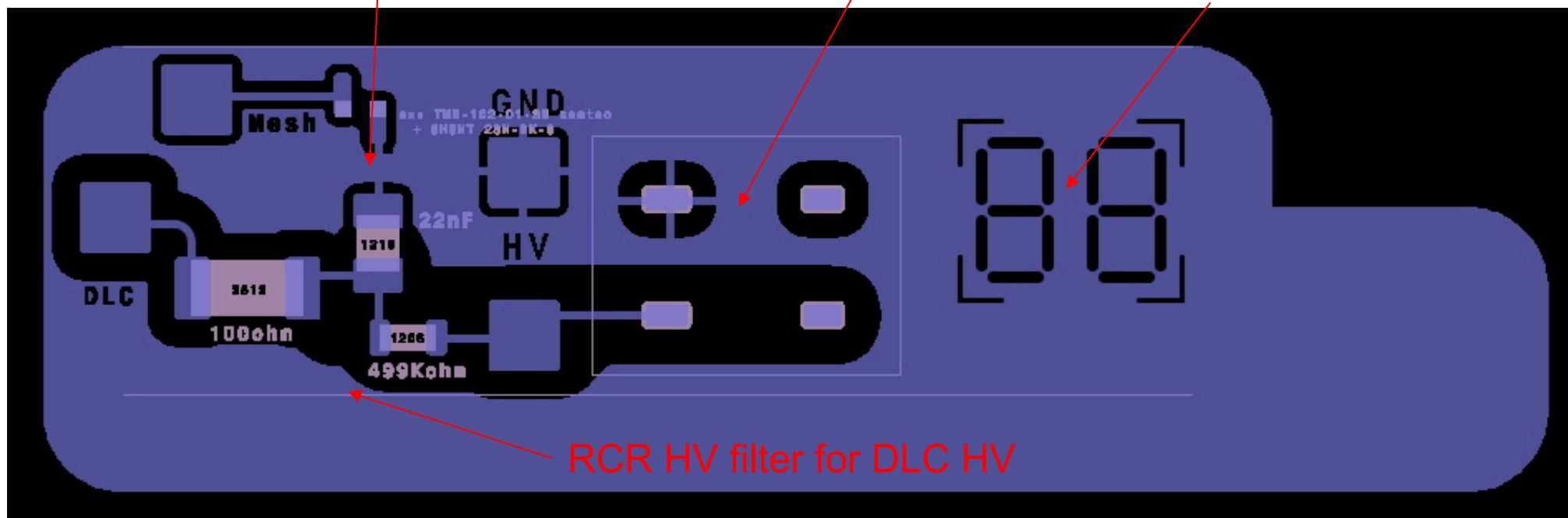


Removable Mesh connection  
to GND for pulse injection on mesh

connector

ref: CERN/IRFU – DFS2278  
Top layer, upper left corner

ERAM S/N



ERAM#01 RCR cabled filter  
(january 18, 2020)



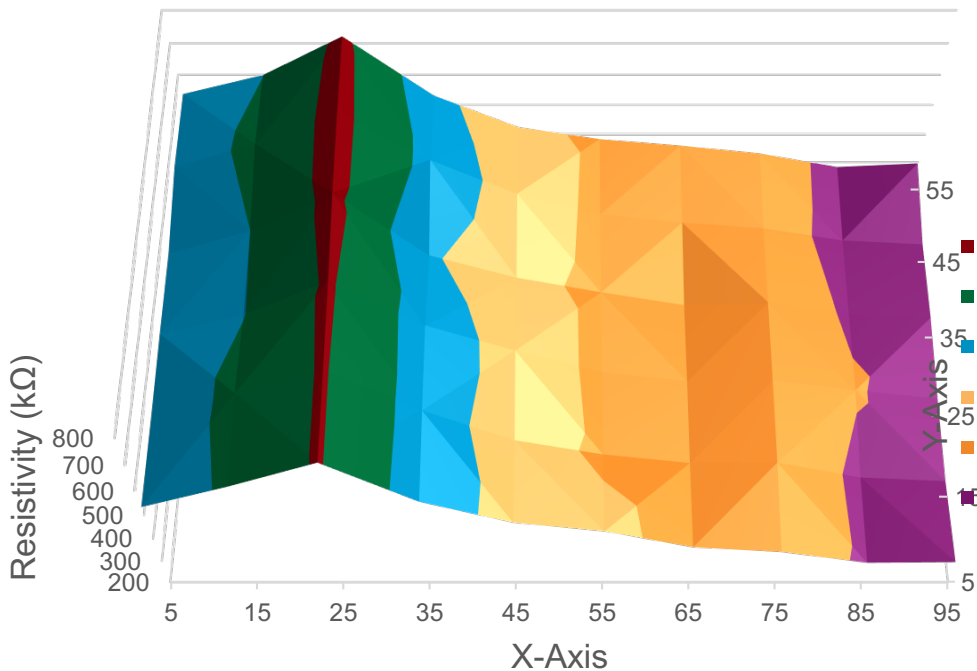
# Resistivity measurements of foil #1 & #3 With CERN custom made probe



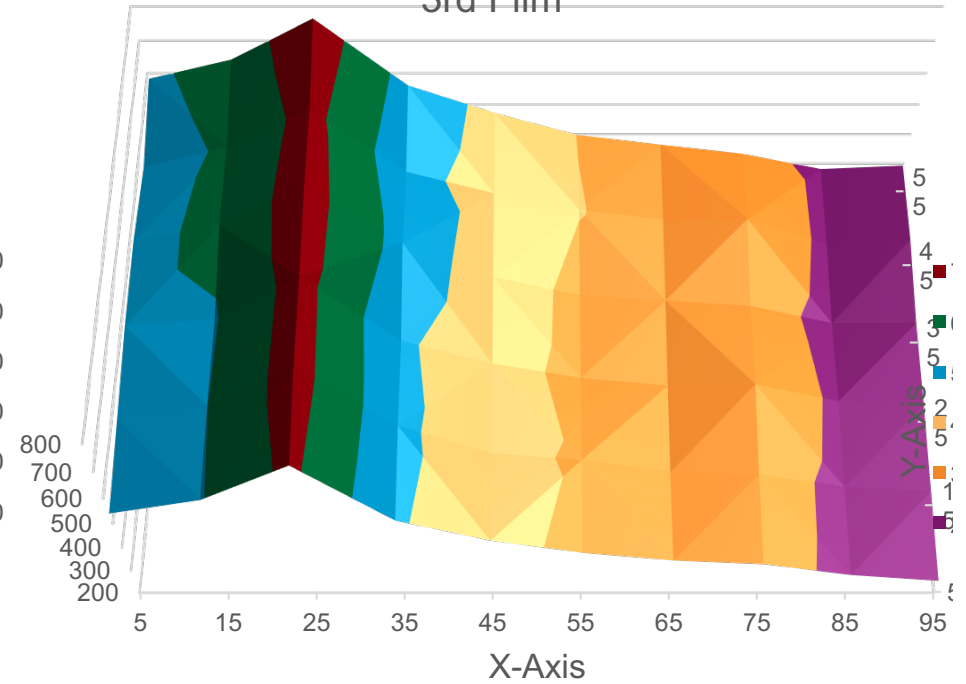
1st Film	5	15	25	35	45	55	65	75	85	95	3rd Film	5	15	25	35	45	55	65	75	85	95
5	532	615	708	554	467	430	360	339	290	293	5	540	593	723	512	430	378	345	329	281	255
15	526	625	708	559	442	384	348	350	286	270	15	554	599	742	526	419	392	342	333	282	264
25	525	597	712	556	462	377	342	346	305	270	25	569	593	738	516	432	378	348	354	287	273
35	520	600	726	512	431	376	327	338	293	278	35	570	625	745	565	445	380	360	340	275	275
45	546	623	728	570	453	380	349	328	282	267	45	547	615	733	532	460	403	368	370	283	296
55	537	599	721	532	425	383	360	332	283	296	55	582	642	765	561	472	398	365	334	280	292

Ref: Elcin Akar (CERN/EP-DT-EF)

1st Film



3rd Film



# Comparison with previous "ochi" probe measurements

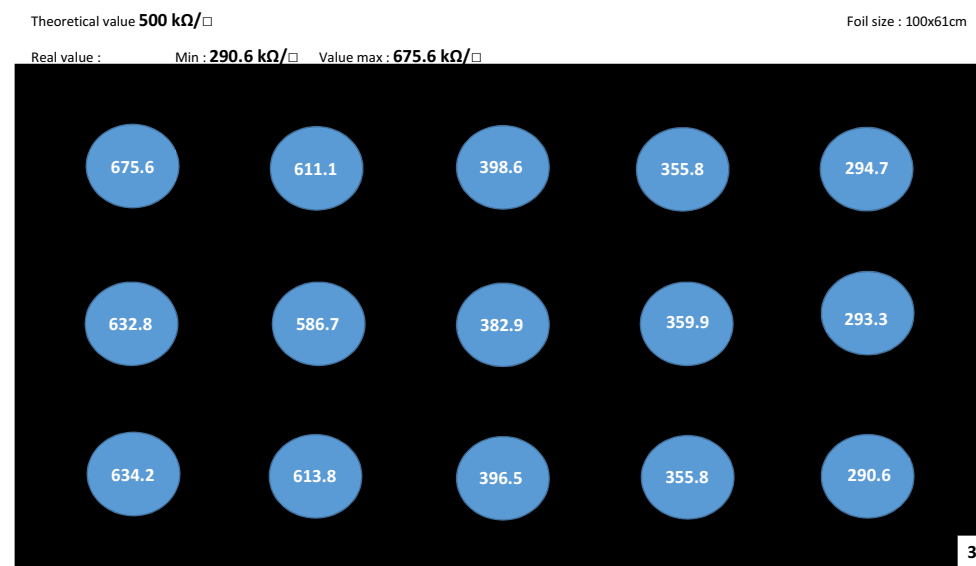
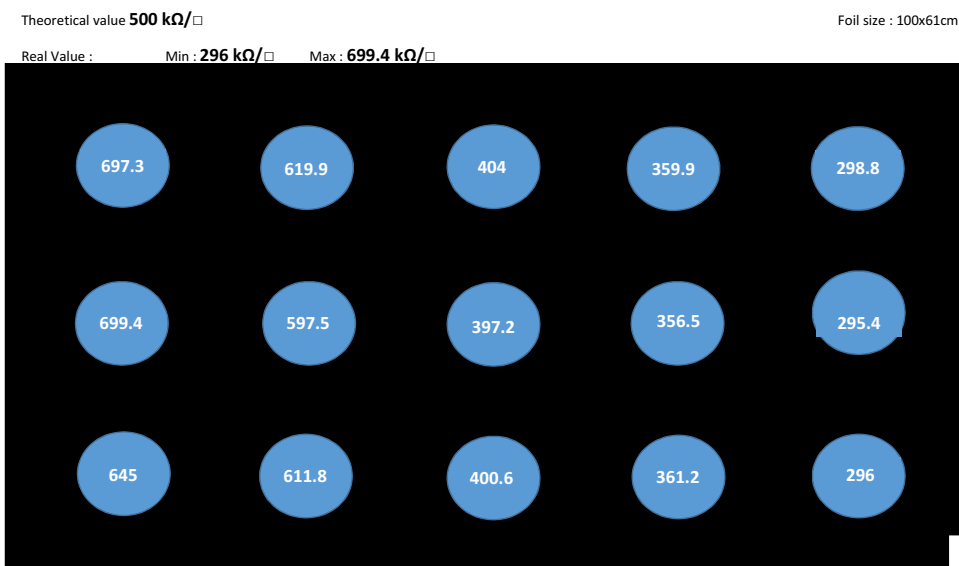


## CERN Custom made probe

1st Film	5	15	25	35	45	55	65	75	85	95	3rd Film	5	15	25	35	45	55	65	75	85	95
5	532	615	708	554	467	430	360	339	290	293	5	540	593	723	512	430	378	345	329	281	255
15	526	625	708	559	442	384	348	350	286	270	15	554	599	742	526	419	392	342	333	282	264
25	525	597	712	556	462	377	342	346	305	270	25	569	593	738	516	432	378	348	354	287	273
35	520	600	726	512	431	376	327	338	293	278	35	570	625	745	565	445	380	360	340	275	275
45	546	623	728	570	453	380	349	328	282	267	45	547	615	733	532	460	403	368	370	283	296
55	537	599	721	532	425	383	360	332	283	296	55	582	642	765	561	472	398	365	334	280	292

Ref: Elcin Akar (CERN/EP-DT-EF)

CERN « Ochi » probe (2018) → 10-20 % higher



Part of DLC foil #5 used for MM1-DLC2 (same as DLC1 at 10%)

Foil size : 100x61cm

Theoretical value **500 kΩ/□**

Real value : Min : **323.2 kΩ/□** Max : **727.9 kΩ/□**



In blue boxes: measured value outside detector area once detector is finished

## MM1-DLC2 resistivity – active area side

PCB N°2 - MM1-DLC N°2  
feuille N°5

Les valeurs affichées ne tiennent pas compte du coefficient de l'appareil qui est de 6.79

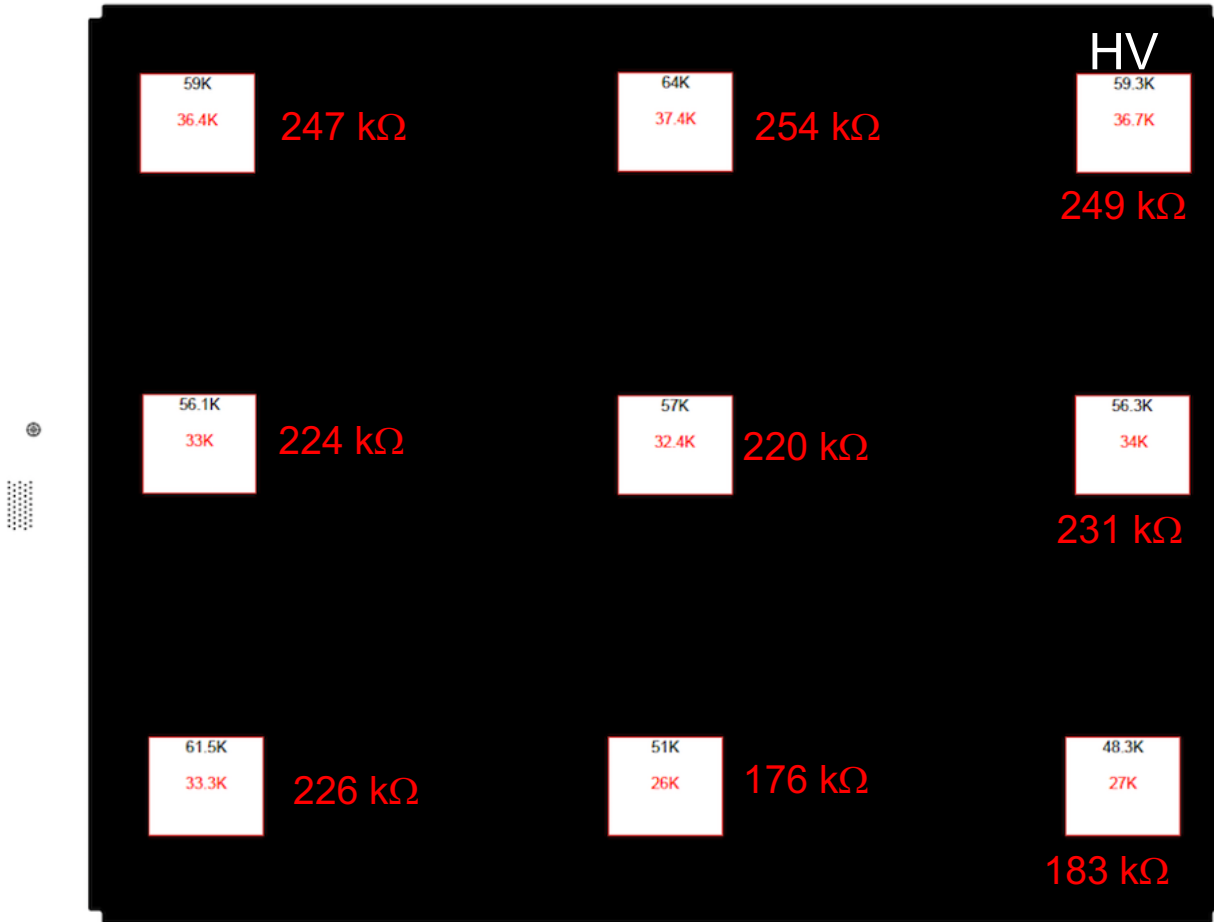
221 kΩ  
3 / 265 kΩ

72.4K  
37.7K  
39K

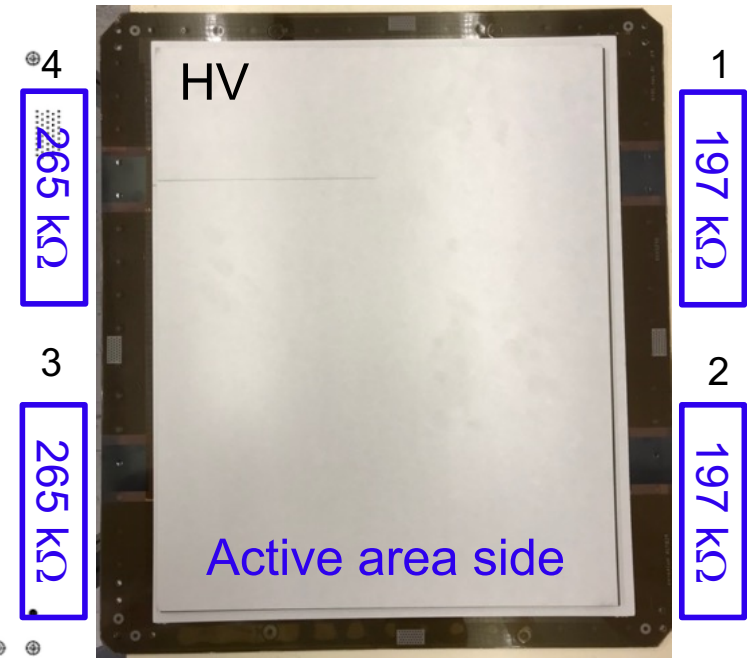
222 kΩ  
4 / 265 kΩ

73.5K  
42K  
39K

Same resistivity as DLC1 !



MM1-DLC2 resistivity (CERN "ochi" probe, k=6,79)



166 kΩ

49.5K  
34K  
29K

Mesures avant pressage

Mesures après pressage

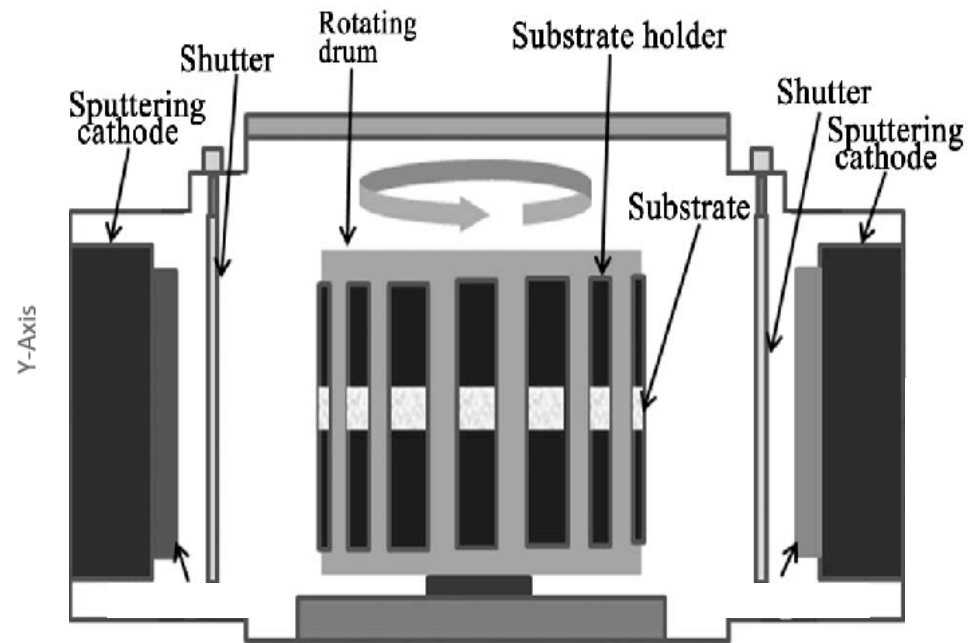
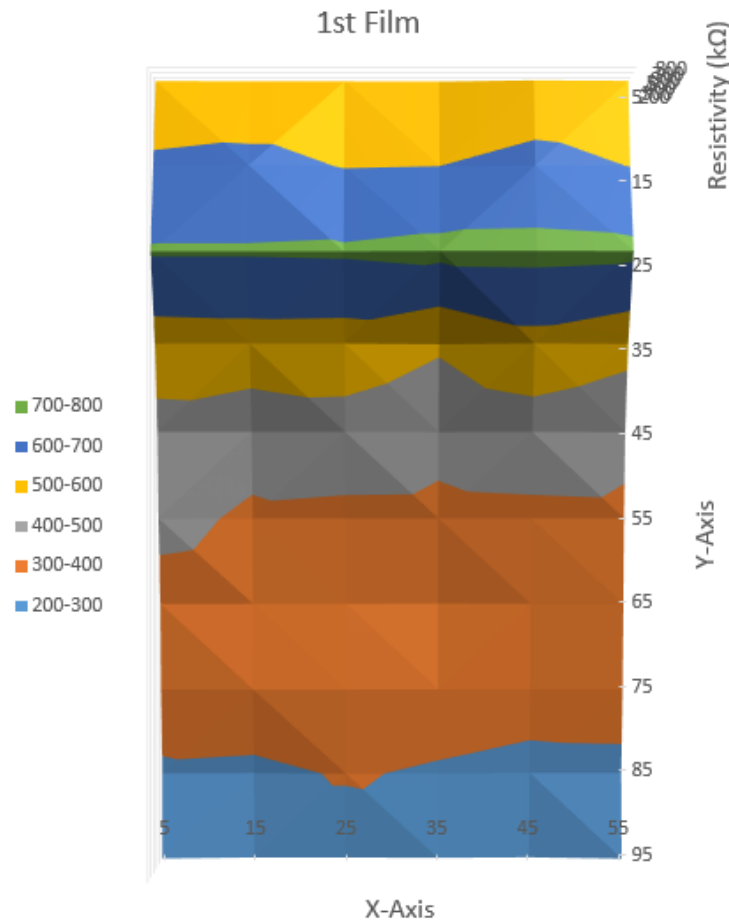
Mesures après soudage

170 kΩ

50.5K  
30K  
29K

1 / 197 kΩ





Schematic representation of magnetron sputtering mechanism.